

```
=> fil hcaplus
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FILE COVERS 1907 - 17 Jul 2008 VOL 149 ISS 3
FILE LAST UPDATED: 16 Jul 2008 (20080716/ED)
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=> d 175 bib abs hitstr retable tot
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L75 ANSWER 1 OF 5 HCAPLUS COPYRIGHT 2008 ACS on STN
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AN 2006:1333714 HCAPLUS
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DN 146:71905
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TI Positive-working presensitized lithographic plates forming less
development scums and showing good ink wettability
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IN Kakino, Ryuki
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PA Fujifilm Holdings Corp., Japan
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SO Jpn. Kokai Tokkyo Koho, 64pp.
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CODEN: JKXXAF
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DT Patent
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LA Japanese
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FAN.CNT 1
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	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2006343667	A	20061221	JP 2005-171175	20050610
PRAI	JP 2005-171175		20050610		

```
AB The plates have pos. photosensitive layers containing (i) macromols. having
unit (CH2)nRf [Rf = substituents containing F≥9 (per)fluoroalkyl; n =
1-3], COOR1 (R1 = aryl, alkyl, or acyl giving R1OH with pKa 3-9), and
monovalent sidechains having ≥6 C atoms and (ii) IR absorbers.
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IT 916659-81-9 916659-89-7
```

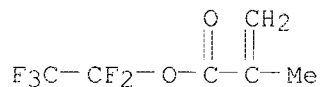
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RL: TEM (Technical or engineered material use); USES (Uses)
(upper photosensitive layers; pos. PS plates containing fluoroalkyl-, long
sidechain-, and ester- or acyl-containing polymers and forming less scums)
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RN 916659-81-9 HCAPLUS
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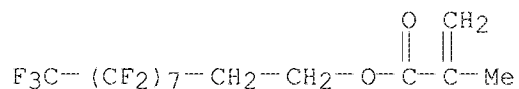
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CN 2-Propenoic acid, 2-methyl-, dodecyl ester, polymer with
3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl
2-methyl-2-propenoate and 1,1,2,2,2-pentafluoroethyl 2-methyl-2-propenoate
(CA INDEX NAME)
```

17 july 2008

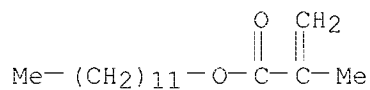
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 CRN 88473-48-7
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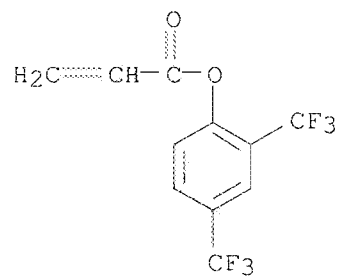
 CRN 1996-88-9
 CMF C14 H9 F17 O2


CM 3

 CRN 142-90-5
 CMF C16 H30 O2


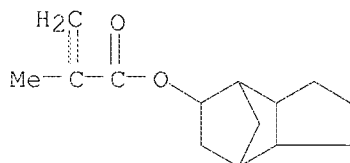
RN 916659-89-7 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, octahydro-4,7-methano-1H-inden-5-yl ester,
 polymer with 2,4-bis(trifluoromethyl)phenyl 2-propenoate and
 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-propenoate (CA INDEX NAME)

CM 1

 CRN 916659-88-6
 CMF C11 H6 F6 O2


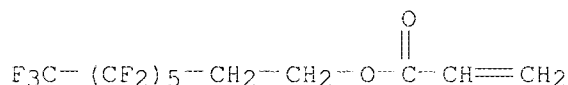
CM 2

CRN 34759-34-7
CMF C14 H20 O2



CM 3

CRN 17527-29-6
CMF C11 H7 F13 O2



L75 ANSWER 2 OF 5 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 2004:612326 HCAPLUS

DN 141:147887

TI Optical component derived from polymerizable composition and optical communication system

IN Okazaki, Masaki; Hayakawa, Toshiro

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 24 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004212722	A	20040729	JP 2003-519	20030106 <--
PRAI	JP 2003-519		20030106	<--	

AB The invention relates to a polymerizable composition, suited for use in making an optical fiber for a red-emitting semiconductor laser, comprising a polymerization initiator and a polymerizable monomer represented by $X1X1C=CY1(COOR1)$ [X = H or D, and both X may differ; Y = H, D, CH3, and CD3; R1 = C7-20 alicyclic hydrocarbons], addnl. the composition may contain a polymerizable monomer in which R1 is a C1-7 fluoroalkyl group.

IT 671232-52-3P 727668-38-4P 727668-39-5P
727668-40-8P

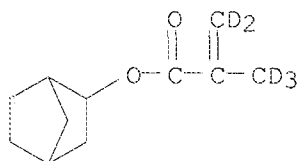
RL: DEV (Device component use); PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (optical fiber derived from polymerizable composition for optical communication system)

RN 671232-52-3 HCAPLUS

CN 2-Propenoic-3,3-d2 acid, 2-(methyl-d3)-, bicyclo[2.2.1]hept-2-yl ester, polymer with 2,2,2-trifluoroethyl 2-(methyl-d3)-2-propenoate-3,3-d2 (9CI) (CA INDEX NAME)

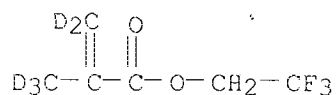
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CRN 117205-77-3
CMF C11 H11 D5 O2



CM 2

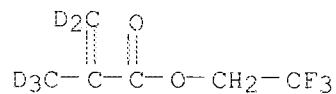
CRN 103243-23-8
CMF C6 H2 D5 F3 O2



RN 727668-38-4 HCAPLUS
CN 2-Propenoic-3,3-d2 acid, 2-(methyl-d3)-, 2,2,2-trifluoroethyl ester, polymer with 2,2,2-trifluoroethyl 2-methyl-2-propenoate and 1,7,7-trimethylbicyclo[2.2.1]hept-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

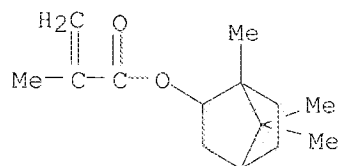
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CRN 103243-23-8
CMF C6 H2 D5 F3 O2



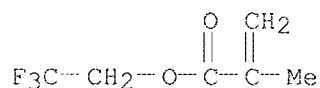
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CRN 16868-12-5
CMF C14 H22 O2



CM 3

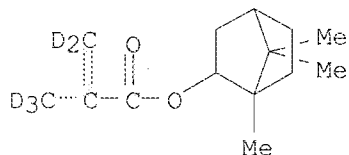
CRN 352-87-4
CMF C6 H7 F3 O2



RN 727668-39-5 HCAPLUS
CN 2-Propenoic-3,3-d2 acid, 2-(methyl-d3)-, 2,2,2-trifluoroethyl ester, polymer with 2,2,2-trifluoroethyl 2-methyl-2-propenoate and 1,7,7-trimethylbicyclo[2.2.1]hept-2-yl 2-(methyl-d3)-2-propenoate-3,3-d2 (9CI) (CA INDEX NAME)

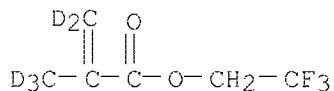
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CRN 711305-16-7
CMF C14 H17 D5 O2



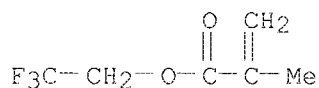
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CRN 103243-23-8
CMF C6 H2 D5 F3 O2



CM 3

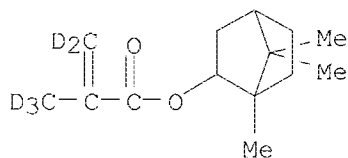
CRN 352-87-4
CMF C6 H7 F3 O2



RN 727668-40-8 HCAPLUS
CN 2-Propenoic-3,3-d2 acid, 2-(methyl-d3)-, 2,2,2-trifluoroethyl ester, polymer with 2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-(methyl-d3)-2-propenoate-3,3-d2 acid and 1,7,7-trimethylbicyclo[2.2.1]hept-2-yl 2-(methyl-d3)-2-propenoate-3,3-d2 (9CI) (CA INDEX NAME)

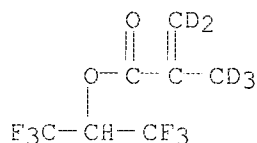
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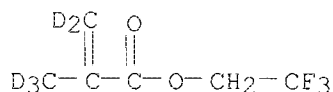
CM 2

CRN 103243-27-2
CMF C7 H D5 F6 O2



CM 3

CRN 103243-23-8
CMF C6 H2 D5 F3 O2



L75 ANSWER 3 OF 5 HCAPLUS COPYRIGHT 2008 ACS on STN
AN 2004:220376 HCAPLUS
DN 140:254366
TI Fluoropolymers for optical members, processes for their preparation, and compositions of the polymers
IN Sasaki, Hiroki; Nemori, Ryoichi
PA Fuji Photo Film Co., Ltd., Japan
SO PCT Int. Appl., 84 pp.
CODEN: PIXXD2
DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2004022614	A2	20040318	WO 2003-JP11301	20030904 <--
	WO 2004022614	A3	20040708		
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM, PG, PH,				

17 july 2008

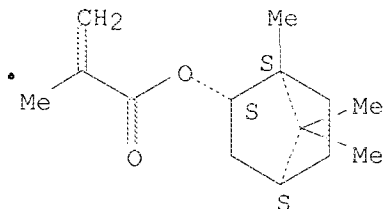
PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT,
 TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
 RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY,
 KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES,
 FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR,
 BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG
 JP 2004099652 A 20040402 JP 2002-259862 20020905 <--
 JP 2004151661 A 20040527 JP 2002-348128 20021129 <--
 AU 2003259570 A1 20040329 AU 2003-259570 20030904 <--
 EP 1534762 A2 20050601 EP 2003-794229 20030904 <--
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 IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK
 CN 1681861 A 20051012 CN 2003-821262 20030904 <--
 US 20060173148 A1 20060803 US 2005-526381 20051027 <--
 PRAI JP 2002-259862 A 20020905 <--
 JP 2002-259863 A 20020905 <--
 JP 2002-348128 A 20021129 <--
 WO 2003-JP11301 W 20030904 <--
 AB A polymerizable composition comprises (A) X12C:CY1CO2R1 and (B) X22C:CY2CO2R2
 where X1 and X2 resp. denote hydrogen (H) or deuterium (D) and two X1s and
 two X2s may be identical or different each other; Y1 and Y2 resp. denote
 H, D, CH3, CD3 or fluorine (F); R1 is a branched C3-8 alkyl group; R2 is a
 C1-7 fluoroalkyl group substituted with 1 to 15 fluorine atoms; and the
 compound (A) to the compound (B) mole ratio is not less than 1/100 and less
 than 4/1; and a polymerization initiator capable of initiating polymerization
 of the
 polymerizable monomer composition Processes for preparing an optical member
 comprising polymerization of a composition comprising the monomer (A) or the
 monomer
 (3) are also disclosed.
 IT 671232-50-1P 671232-51-2P 671232-52-3P
 671232-96-5P 671232-97-6P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material
 use); PREP (Preparation); USES (Uses)
 (fluoropolymers for optical members, processes for their preparation, and
 compns. of the polymers)
 RN 671232-50-1 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, 2,2,2-trifluoro-1-(trifluoromethyl)ethyl
 ester, polymer with rel-(1R,2R,4R)-1,7,7-trimethylbicyclo[2.2.1]hept-2-yl
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 7534-94-3

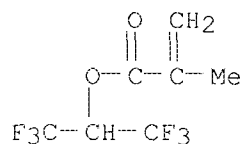
CMF C14 H22 O2

Relative stereochemistry.



CM 2

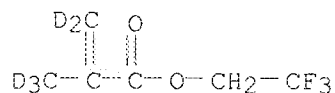
CRN 3063-94-3
CMF C7 H6 F6 O2



RN 671232-51-2 HCAPLUS
CN 2-Propenoic-3,3-d2 acid, 2-(methyl-d3)-, 2,2,2-trifluoroethyl ester, polymer with 2,2,2-trifluoroethyl 2-methyl-2-propenoate and rel-(1R,2R,4R)-1,7,7-trimethylbicyclo[2.2.1]hept-2-yl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

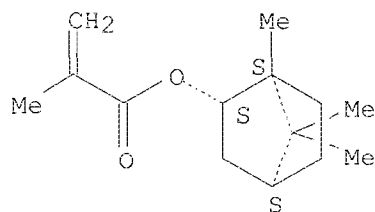
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CMF C6 H2 D5 F3 O2



CM 2

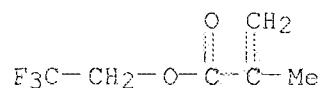
CRN 7534-94-3
CMF C14 H22 O2

Relative stereochemistry.



CM 3

CRN 352-87-4
CMF C6 H7 F3 O2



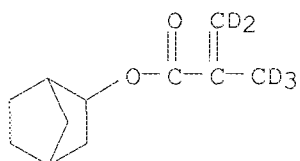
RN 671232-52-3 HCAPLUS

CN 2-Propenoic-3,3-d2 acid, 2-(methyl-d3)-, bicyclo[2.2.1]hept-2-yl ester, polymer with 2,2,2-trifluoroethyl 2-(methyl-d3)-2-propenoate-3,3-d2 (9CI) (CA INDEX NAME)

CM 1

CRN 117205-77-3

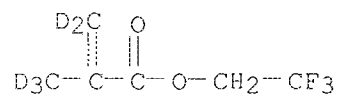
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CM 2

CRN 103243-23-8

CMF C6 H2 D5 F3 O2



RN 671232-96-5 HCAPLUS

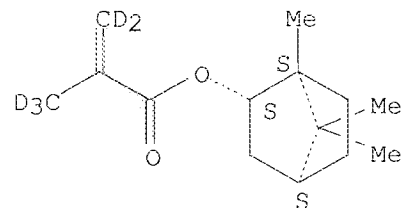
CN 2-Propenoic-3,3-d2 acid, 2-(methyl-d3)-, 2,2,2-trifluoroethyl ester, polymer with 2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-(methyl-d3)-2-propenoate-3,3-d2 and rel-(1R,2R,4R)-1,7,7-trimethylbicyclo[2.2.1]hept-2-yl 2-(methyl-d3)-2-propenoate-3,3-d2 (9CI) (CA INDEX NAME)

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CRN 671232-95-4

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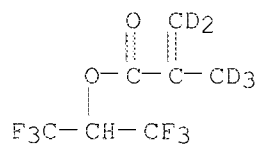
Relative stereochemistry.



CM 2

CRN 103243-27-2

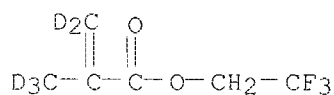
CMF C7 H D5 F6 O2



CM 3

CRN 103243-23-8

CMF C6 H2 D5 F3 O2



RN 671232-97-6 HCAPLUS

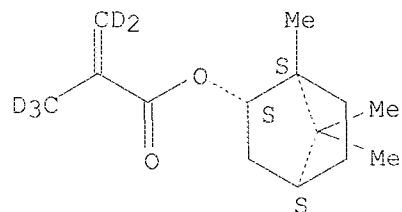
CN 2-Propenoic-3,3-d2 acid, 2-(methyl-d3)-, 2,2,2-trifluoroethyl ester,
 polymer with 2,2,2-trifluoroethyl 2-methyl-2-propenoate and
 rel-(1R,2R,4R)-1,7,7-trimethylbicyclo[2.2.1]hept-2-yl 2-(methyl-d3)-2-
 propenoate-3,3-d2 (9CI) (CA INDEX NAME)

CM 1

CRN 671232-95-4

CMF C14 H17 D5 O2

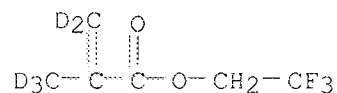
Relative stereochemistry.



CM 2

CRN 103243-23-8

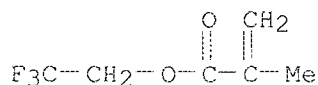
CMF C6 H2 D5 F3 O2



CM 3

CRN 352-87-4

CMF C6 H7 F3 O2

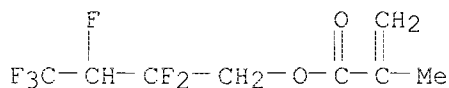


L75 ANSWER 4 OF 5 HCAPLUS COPYRIGHT 2008 ACS on STN
 AN 2003:391202 HCAPLUS
 DN 138:409321
 TI Liquid developer for electrostatography used for printing plate making system
 IN Kato, Eiichi
 PA **Fuji Photo Film Co., Ltd., Japan**
 SO Jpn. Kokai Tokkyo Koho, 32 pp.
 CODEN: JKXXAF
 DT **Patent**
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003149873	A	20030521	JP 2001-348923	20011114 <--
PRAI	JP 2001-348923		20011114	<--	
AB	The liquid developer comprises resin particles dispersed in a nonaq. solvent having an elec. resistivity $\geq 10^9 \Omega \cdot \text{cm}$ and a dielec. constant ≤ 3.5 . The dispersed resin is obtained by seed polymerization of ≥ 1 monofunctional monomer (A) soluble in said solvent and becoming insol. upon polymerization, a monofunctional monomer (B) which is polymerizable with (A) and contains F- and/or Si-containing substituent, and [HCb1-Cb2(V0-L)] (V0 = COO, OCO, etc.; b1,2 = H, halo, cyano, etc.; L = C8-32 alkyl, alkenyl, etc.) in the presence of a colloidal dispersion stabilizing resin (P) with an. average grain diameter 0.05-1.0 μm as a seed particle. The liquid developer made the development-fixing steps faster.				
IT	528812-10-4P 528812-12-6P 528812-23-9P RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (dispersion stabilizing resin; liquid developer for electrostatog. used for printing plate making system)				
RN	528812-10-4 HCAPLUS				
CN	2-Propenoic acid, 2-methyl-, 2,2,3,4,4,4-hexafluorobutyl ester, polymer with phenylmethyl 2-methyl-2-propenoate and phenylmethyl 2-propenoate (9CI) (CA INDEX NAME)				

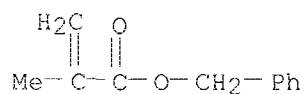
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CRN 36405-47-7
 CMF C8 H8 F6 O2



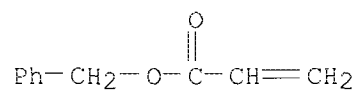
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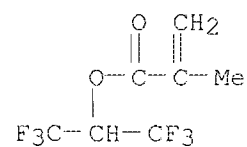
CRN 2495-35-4
CMF C10 H10 O2



RN 528812-12-6 HCAPLUS
CN 2-Propenoic acid, 2-methyl-, phenylmethyl ester, polymer with phenylmethyl
2-propenoate and 2,2,2-trifluoro-1-(trifluoromethyl)ethyl
2-methyl-2-propenoate (9CI) (CA INDEX NAME)

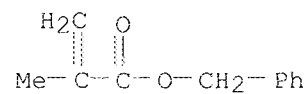
CM 1

CRN 3063-94-3
CMF C7 H6 F6 O2



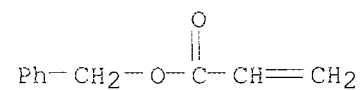
CM 2

CRN 2495-37-6
CMF C11 H12 O2



CM 3

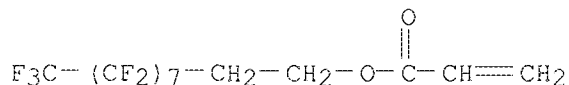
CRN 2495-35-4
CMF C10 H10 O2



RN 528812-23-9 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, phenylmethyl ester, polymer with
 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and
 phenylmethyl 2-propenoate (9CI) (CA INDEX NAME)

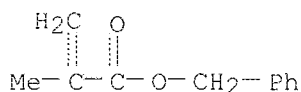
CM 1

CRN 27905-45-9
 CMF C13 H7 F17 O2



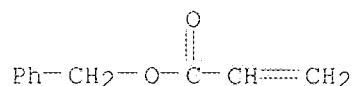
CM 2

CRN 2495-37-6
 CMF C11 H12 O2



CM 3

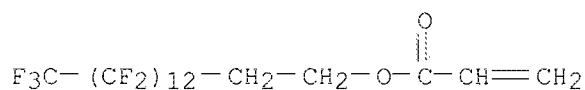
CRN 2495-35-4
 CMF C10 H10 O2



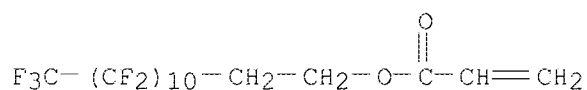
L75 ANSWER 5 OF 5 HCAPLUS COPYRIGHT 2008 ACS on STN
 AN 1997:44689 HCAPLUS
 DN 126:67571
 OREF 126:12989a,12992a
 TI Image-receiving sheet for thermal-transfer recording
 IN Ishizuka, Takahiro; Totsuka, Mikio
 PA **Fuji Photo Film Co Ltd, Japan**
 SO Jpn. Kokai Tokkyo Koho, 8 pp.
 CODEN: JKXXAF
 DT **Patent**
 LA Japanese
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08276674	A	19961022	JP 1995-78687	19950404 <--
PRAI	JP 1995-78687		19950404	<--	
AB	The sheet comprises a support back-coated with a grafted fluoropolymer layer. The sheet having a graft copolymer layer obtained from 1H,1H,2H,2H-perfluorooctyl acrylate and CH ₂ :CMeC(:O)O(CH ₂ CHMeO) _n H (n = 12)				

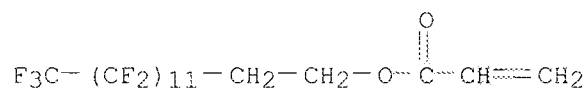
showed good storage stability.
 IT **185245-42-5P**
 RL: DEV (Device component use); MOA (Modifier or additive use); PNU
 (Preparation, unclassified); PREP (Preparation); USES (Uses)
 (image-receiving sheet having grafted fluoropolymer backcoat layer for
 thermal-transfer recording)
 RN 185245-42-5 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, phenylmethyl ester, polymer with
 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,12-heneicosafuorododecyl
 2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,13,14,14,15
 ,15,15-heptacosafuoropentadecyl 2-propenoate,
 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,13,14,14,14-
 pentacosafuorotetradecyl 2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,
 11,11,12,12,13,13,13-tricosafuorotridecyl 2-propenoate and
 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-propenoate, graft (9CI)
 (CA INDEX NAME)
 CM 1
 CRN 137667-55-1
 CMF C18 H7 F27 O2



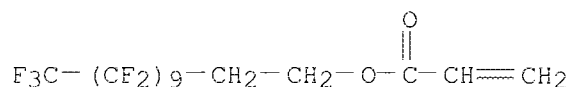
CM 2
 CRN 41328-02-3
 CMF C16 H7 F23 O2



CM 3
 CRN 34395-24-9
 CMF C17 H7 F25 O2



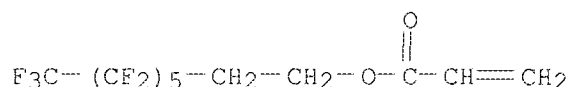
CM 4
 CRN 17741-60-5
 CMF C15 H7 F21 O2



CM 5

CRN 17527-29-6

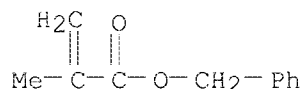
CMF C11 H7 F13 O2



CM 6

CRN 2495-37-6

CMF C11 H12 O2



=> d 176 bib abs hitstr retable tot

L76 ANSWER 1 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 2004:6062 HCAPLUS

DN 140:287782

TI Preparation and characterization of fluoroacrylate copolymer by emulsion polymerization

AU Kim, Dong Ok; Kim, Ji Hyun

CS SK Chemicals Research Institute, Kyungki-do, S. Korea

SO Polymer (Korea) (2003), 27(6), 528-535

CODEN: POLLDG; ISSN: 0379-153X

PB Polymer Society of Korea

DT Journal

LA Korean

AB The effects of surfactants, organic solvents, and functional monomers on the emulsion polymerization of perfluoroalkylethyl acrylates and n-alkyl acrylates were investigated. The dependency of the surface properties, contact angle, and water repellency on the crystal melting temperature (T_m) of the fluorocopolymer and the variation of polymer latex particle sizes were investigated. Using WAXD expts. and synthesizing different types of fluorocopolymers which have fluoroacrylates $[\text{CH}_2:\text{CHCO}_2\text{CH}_2(\text{CF}_2\text{CF}_2)_n\text{H}]$ ($n = 4, 5$ or 6), the relationship between the mol. packing structure of pendent side groups of the fluorocopolymers and the surface properties was also investigated. We observed that the structure of primary carbon atoms of pendent side groups of the fluorocopolymers plays a key role in determining the surface properties.

IT 675579-57-4P 675579-59-6P

RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)

17 july 2008

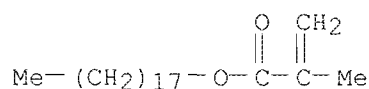
(preparation and characterization of fluoroacrylate copolymer by emulsion polymerization)

RN 675579-57-4 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, octadecyl ester, polymer with dodecyl 2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and octadecyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 32360-05-7

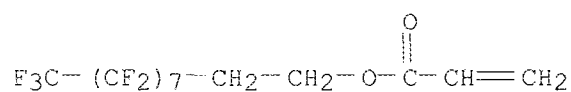
CMF C22 H42 O2



CM 2

CRN 27905-45-9

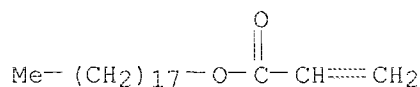
CMF C13 H7 F17 O2



CM 3

CRN 4813-57-4

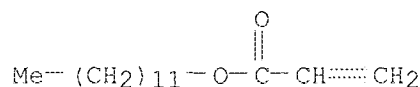
CMF C21 H40 O2



CM 4

CRN 2156-97-0

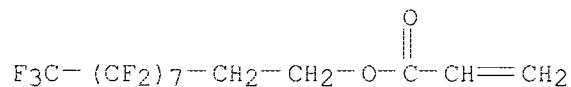
CMF C15 H28 O2



RN 675579-59-6 HCAPLUS
 CN 2-Propenoic acid, dodecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and octadecyl 2-propenoate (9CI) (CA INDEX NAME)

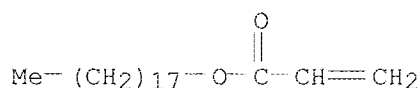
CM 1

CRN 27905-45-9
CMF C13 H7 F17 O2



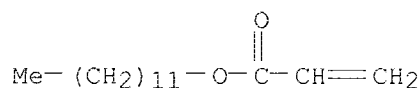
CM 2

CRN 4813-57-4
CMF C21 H40 O2



CM 3

CRN 2156-97-0
CMF C15 H28 O2



L76 ANSWER 2 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN
AN 2002:944841 HCAPLUS
DN 138:25868
TI Water- and oilproofing compositions with long service life
IN Maekawa, Takashige; Shindo, Minako; Tada, Masako
PA Asahi Glass Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 11 pp.
CODEN: JKXXAF

DT **Patent**
LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002356671	A	20021213	JP 2001-164821	20010531 <--
PRAI	JP 2001-164821		20010531	<--	

AB The comps. useful for fabric finishing, are obtained from copolymers of (A) monomers bearing polyfluoroalkyl Rf groups rendering microcryst. m.p. of >100° to its homopolymer, e.g. (meth)acrylate C>10 linear fluoroalkyl esters, and (B) monomers bearing polyfluoroalkyl Rf groups which do not have microcryst. m.p. or have a homopolymer microcryst. m.p. of <30°, e.g. (meth)acrylate C>6 linear fluoroalkyl esters. Thus, heating C6F13C2H4OCOCH:CH2 (no homopolymer microcryst. m.p.) 1.45 with C10F21C2H4OCOCH:CH2 (homopolymer microcryst. m.p. 125°) 12.25, stearyl acrylate 20.21, hydroxyethyl acrylate 0.69, polyethylene glycol monomethacrylate 0.69, polyethylene glycol octylphenyl ether 20% aqueous solution

17 july 2008

13.78, stearyltriethylammonium chloride 10% aqueous solution 6.89, water 25.83, acetone 17.23, stearyl mercaptan 0.18 and 2,2'-azobis(2-methylpropionamidine) dihydrochloride 0.07 g at 60° for 12 h gave a copolymer solution useful for fabric finishing.

IT 478034-28-5P

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(manufacture of water- and oilproofing compns. with long service life for fabric finishing)

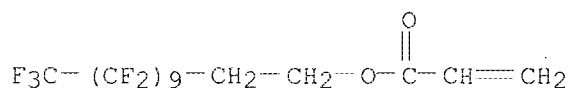
RN 478034-28-5 HCAPLUS

CN 2-Propenoic acid, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,12-heneicosafuorododecyl ester, polymer with octadecyl 2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-propenoate, graft (9CI)
(CA INDEX NAME)

CM 1

CRN 17741-60-5

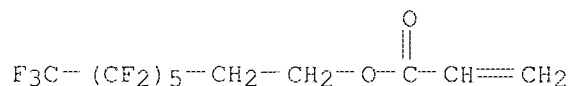
CMF C15 H7 F21 O2



CM 2

CRN 17527-29-6

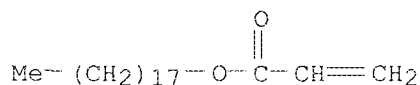
CMF C11 H7 F13 O2



CM 3

CRN 4813-57-4

CMF C21 H40 O2



L76 ANSWER 3 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 2002:711115 HCAPLUS

DN 137:234135

TI Fluoropolymer-containing water-resistant sheet for wallpaper

IN Nakamura, Tetsuya; Tasaka, Tomohisa; Sugiura, Motoyuki

PA NOF Corporation, Japan

SO Jpn. Kokai Tokkyo Koho, 13 pp.

CODEN: JKXXAF

DT Patent

17 july 2008

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002266257	A	20020918	JP 2001-73707	20010315 <--
PRAI	JP 2001-73707		20010315	<--	

AB The sheet comprises a substrate and a surface layer containing blocked fluoropolymer. Thus, a block copolymer for coating on PVC wallpaper was made by the block polymerization of MMA, Bu methacrylate, 2-hydroxyethyl methacrylate, methacrylic acid, and CH₂:CHCOO(CH₂)₂(CF₂)₇CF₃ in the presence of a polymeric peroxide.

IT 459409-60-0P

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(fluoropolymer-containing water-resistant sheet for wallpaper)

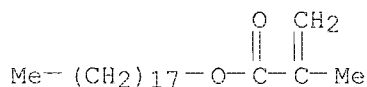
RN 459409-60-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, dodecyl ester, polymer with
3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-propenoate and octadecyl 2-methyl-2-propenoate, block (9CI) (CA INDEX NAME)

CM 1

CRN 32360-05-7

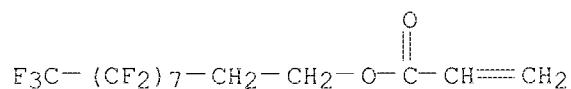
CMF C22 H42 O2



CM 2

CRN 27905-45-9

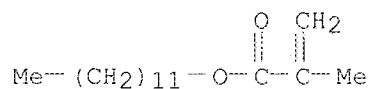
CMF C13 H7 F17 O2



CM 3

CRN 142-90-5

CMF C16 H30 O2



L76 ANSWER 4 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

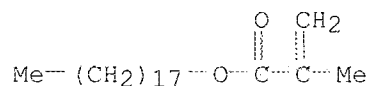
AN 2002:250780 HCAPLUS

DN 136:402261

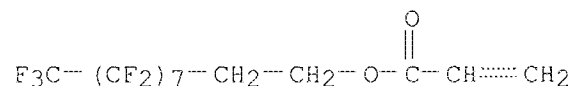
TI Structure of fluorinated side-chain smectic copolymers: role of the

17 july 2008

copolymerization statistics
 AU de Crevoisier, G.; Fabre, P.; Leibler, L.; Tence-Girault, S.; Corpart, J.
 M.
 CS UMR 167 CNRS-ATOFINA-ESPCI, Paris, 75031, Fr.
 SO Macromolecules (2002), 35(10), 3880-3888
 CODEN: MAMOBX; ISSN: 0024-9297
 PB American Chemical Society
 DT Journal
 LA English
 AB Side-chain fluorinated copolymers present very specific wetting and
 tacking properties that are strongly related to their organization. We
 have studied the structure of these systems by X-ray scattering in the
 liquid crystalline regime, as a function of the ratio of fluorinated groups on
 one hand and of the copolymn. statistics on the other. The structures
 obtained are always highly ordered and exhibit a smectic B type
 organization, where the two types of pendant groups are able to
 crystallize independently. However, packing differences appear for
 copolymers with different chain statistics due to the existence of
 microphase separation between the side groups. The roles of these parameters
 on phase transitions, periodicity, and degree of crystallinity of the
 polymers are discussed. Their behavior with temperature, important for
 applications, is also studied.
 IT 428966-26-1
 RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP
 (Physical process); PROC (Process)
 (solution-polymerized; fluorinated side-chain smectic copolymers structure)
 RN 428966-26-1 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, hexadecyl ester, polymer with
 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,12-heneicosafuorododecyl
 2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorododecyl
 2-propenoate, octadecyl 2-methyl-2-propenoate and
 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-propenoate (9CI) (CA INDEX
 NAME)
 CM 1
 CRN 32360-05-7
 CMF C22 H42 O2

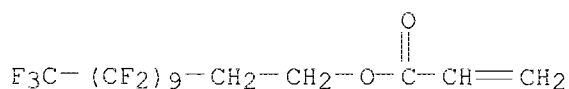


CM 2
 CRN 27905-45-9
 CMF C13 H7 F17 O2



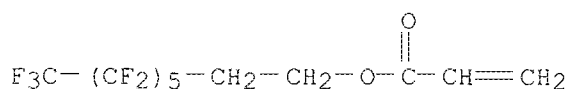
CM 3

CRN 17741-60-5
CMF C15 H7 F21 O2



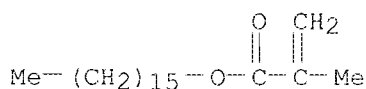
CM 4

CRN 17527-29-6
CMF C11 H7 F13 O2



CM 5

CRN 2495-27-4
CMF C20 H38 O2



RETABLE

Referenced Author (RAU)	Year (RPY)	VOL (RVL)	PG (RPG)	Referenced Work (RWK)	Referenced File
Alig, I	1998	31	2245	Macromolecules	HCAPLUS
Antonietti, M	1997	48	262	Acta Polym	HCAPLUS
Bates, F	1999		32	Phys Today	HCAPLUS
Benoit, H	1988	21	1449	Macromolecules	HCAPLUS
Davidson, P	1988	3	1583	Liq Cryst	HCAPLUS
de Crevoisier, G	1999	285	1246	Science	HCAPLUS
de Crevoisier, G	1999			These de Doctorat, U	
Duda, G	1988	159	221	Thin Solid Films	HCAPLUS
Greenberg, S	1954	76	6280	J Am Chem Soc	HCAPLUS
Guinier, A	1956			Theorie et technique	
Hsieh, H	1976	14	1241	J Polym Sci, Polym P	HCAPLUS
Jordan, E	1971	9	3349	J Polym Sci, Part A1	HCAPLUS
Kaufman, H	1948	70	3147	J Am Chem Soc	HCAPLUS
Krupers, M	1997	198	2163	Macromol Chem Phys	HCAPLUS
Leibler, L	1980	13	1602	Macromolecules	HCAPLUS
Mao, G	1997	48	405	Acta Polym	HCAPLUS
Meakawa, T	1991			Proc XIIIth Symposiu	
Melas, M	1995			These de Doctorat, U	
Milner, S	1994	27	2333	Macromolecules	HCAPLUS
Murthy, N	1990	31	996	Polymer	HCAPLUS
Neumann, H	1993	26	2489	Macromolecules	HCAPLUS
Ober, C	1997	118	701	Macromol Symp	HCAPLUS
Percec, V	1992	A29	723	J Mater Sci, Pure Ap	HCAPLUS

Plate, N	1971 9	2291	J Polym Sci, Part A1
Plate, N	1968 23	37	J Polym Sci, Part C
Poser, S	1996 32	1169	Eur Polym J
Pugh, C	1997 22	610	Prog Polym Sci
Shibasaki, Y	1982 2	1517	Therm Anal, Proc Int HCAPLUS
Shimizu, T	1994 82	173	Macromol Symp HCAPLUS
Volkov, V	1992 33	1316	Polymer HCAPLUS

L76 ANSWER 5 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 2002:244728 HCAPLUS

DN 136:280231

TI Long-lasting water-repellent fluorine-containing block copolymer-based compositions for moldings as artificial marble

IN Nakamura, Tetsuya; Tasaka, Tomohisa; Sugiura, Motoyuki

PA NOF Corporation, Japan

SO Jpn. Kokai Tokkyo Koho, 14 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002097338	A	20020402	JP 2000-288120	20000922 <--
PRAI	JP 2000-288120		20000922	<--	

AB The compns. comprise mainly 0.05-30 parts a fluorine block-copolymer (A) and 70-99.95 parts a curable resin (B), wherein A contains segments of block copolymer of Cl2-20 F-containing monomer and long alkyl (meth)acrylates. Thus, block-polymerizing Me methacrylate 200, Bu methacrylate 200, 2-hydroxyethyl methacrylate 70, and methacrylic acid 30 g with homopolymer of (perfluorooctyl)ethyl acrylate 500 g gave an A, 0.5 parts of which was mixed with 100 parts Epolac G 110AL (an unsatd. polyester, B component) and 200 parts aluminum hydroxide and cured in the presence of 2 parts Me Et ketone peroxide and 0.5 parts cobalt naphthenate to give a title composition

IT **406497-72-1P**, Dodecyl methacrylate-octadecyl acrylate-octadecyl methacrylate-(perfluorooctyl)ethyl acrylate block copolymer
 RL: IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); POF (Polymer in formulation); PRP (Properties); PYP (Physical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)

(also in surface coating; long-lasting water-repellent fluorine-containing block copolymer-based compns. for moldings as artificial marble)

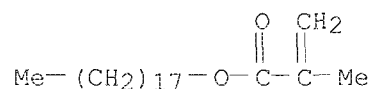
RN 406497-72-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, dodecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-propenoate, octadecyl 2-methyl-2-propenoate and octadecyl 2-propenoate, block (9CI) (CA INDEX NAME)

CM 1

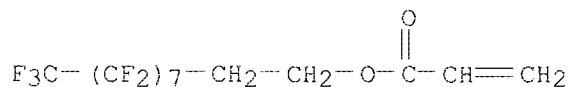
CRN 32360-05-7

CMF C22 H42 O2



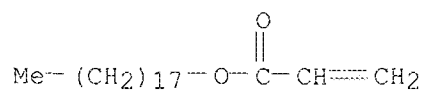
CM 2

CRN 27905-45-9
CMF C13 H7 F17 O2



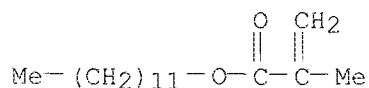
CM 3

CRN 4813-57-4
CMF C21 H40 O2



CM 4

CRN 142-90-5
CMF C16 H30 O2



L76 ANSWER 6 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN
AN 2001:798505 HCAPLUS
DN 135:332504
TI Water and oil repellency treatment of fiber product
IN Enomoto, Takashi; Yamamoto, Ikuo; Otsuki, Norihito; Fukuda, Teruyuki;
Kusumi, Kayo
PA Daikin Industries, Ltd., Japan
SO PCT Int. Appl., 32 pp.
CODEN: PIXXD2
DT **Patent**
LA Japanese
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2001081672	A1	20011101	WO 2001-JP3217	20010416 <--
	W: CA, US				
	RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,				
	PT, SE, TR				
	JP 2002004177	A	20020109	JP 2001-23917	20010131 <--
	US 20030115678	A1	20030626	US 2002-258067	20021018 <--
PRAI	JP 2000-119603	A	20000420	<--	
	JP 2001-23917	A	20010131	<--	
	WO 2001-JP3217	W	20010416	<--	

AB The treatment process comprises (1) preparing a treating liquid containing a water

17 july 2008

and oil repellency agent comprising a fluoro compound or polymer and an organic acid salt, (2) adjusting the pH to ≤ 7 (3) applying the treating liquid onto a fiber product, (4) steam treating the fiber, and (5) washing the fiber product with water, followed by dehydrating. Thus, CH₂:CHCOOCH₂CH₂C₆F₁₃/CH₂:CHCOOCH₂CH₂C₈F₁₇/CH₂:CHCOOCH₂CH₂C₁₀F₂₁/CH₂:CHCOOCH₂CH₂C₁₂F₂₅/CH₂:CHCOOCH₂CH₂C₁₄F₂₉ mixture and 15 g stearyl acrylate were polymerized to give a fluoropolymer emulsion which (0.4 g) was mixed with stainblocking agent FX 657 5 g and potassium formate, followed by adding sulfamic acid to adjust pH to 1.5, giving a treatment liquid, which was used for nylon carpet, showing good oil and water repellency.

IT 369647-15-4P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(water and oil repellency treatment of fiber product)

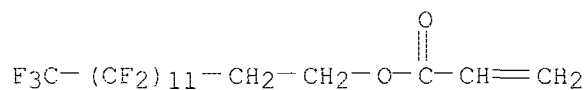
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CN 2-Propenoic acid, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,12-heneicosafuorododecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,13,14,14,15,15,16,16,16-nonacosafuorohexadecyl 2-propenoate, octadecyl 2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,13,14,14,14-pentacosafuorotetradecyl 2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-propenoate (9CI) (CA INDEX NAME)

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CRN 34395-24-9

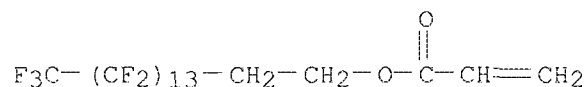
CMF C17 H7 F25 O2



CM 2

CRN 34362-49-7

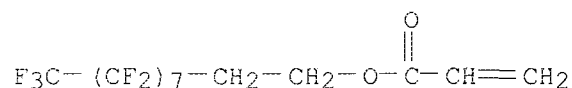
CMF C19 H7 F29 O2



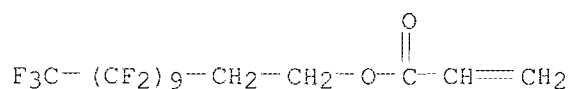
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CRN 27905-45-9

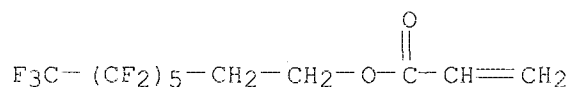
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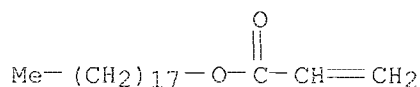
CM 4

 CRN 17741-60-5
 CMF C15 H7 F21 O2


CM 5

 CRN 17527-29-6
 CMF C11 H7 F13 O2


CM 6

 CRN 4813-57-4
 CMF C21 H40 O2


RETABLE

Referenced Author (RAU)	Year (RPY)	VOL (RVL)	PG (RPG)	Referenced Work (RWK)	Referenced File
Dennis, J				WO 96025240 A	
Dennis, J	1998			US 5851595 A	HCAPLUS
Toyobo Co Ltd	1987			JP 6285080 A	

L76 ANSWER 7 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 2000:713092 HCAPLUS

DN 133:297606

TI Oil- and water-repellent resin compositions for textiles

 IN Shindou, Minako; Kaida, Yuriko; Oharu, Kazuya; Shimada, Toyomichi;
 Maekawa, Takashige

PA Asahi Glass Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 15 pp.

CODEN: JKXXAF

 DT **Patent**

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2000282015	A	20001010	JP 2000-19210	20000127 <--
PRAI	JP 1999-20377	A	19990128	<--	
OS	MARPAT 133:297606				

17 july 2008

AB The compns. contain surfactants, aqueous media, and particles of ≥ 2 copolymers (A) of polyfluoroalkyl group-containing (meth)acrylates and OH-containing monomer (solubility ≤ 10 g in 100 mL water at 25°) or polymer particles containing A and other polymers. Thus, an aqueous dispersion was prepared by radical polymerization of $\text{H}_2\text{C}:\text{CHCO}_2\text{CH}_2\text{CH}_2\text{C}_m\text{F}_{2m+1}$ (I; $m = 6, 8, 10, 12, 14, 16$), cyclohexyl methacrylate, and $\text{H}_2\text{C}:\text{CMeCO}_2\text{CH}_2\text{CH}_2\text{O}[\text{CO}(\text{CH}_2)_5\text{O}]_{10}\text{H}$ in the presence of I polymer aqueous dispersion. A nylon fabric treated with this dispersion showed good washfastness.

IT 301199-03-1P

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(oil- and water-repellent acrylic fluoropolymer compns. for textiles)

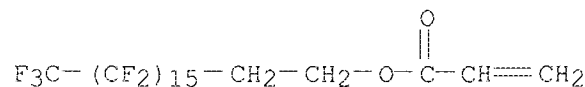
RN 301199-03-1 HCAPLUS

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CM 1

CRN 65150-93-8

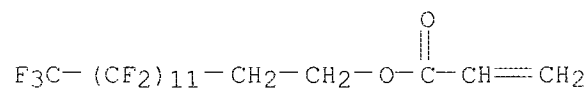
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CM 2

CRN 34395-24-9

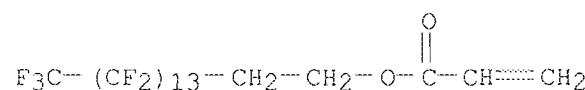
CMF C17 H7 F25 O2



CM 3

CRN 34362-49-7

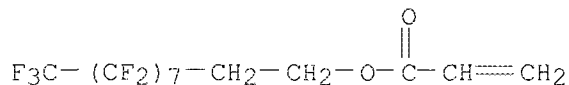
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CM 4

CRN 27905-45-9

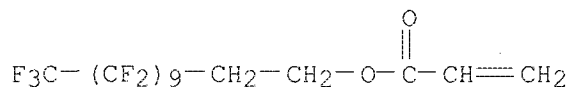
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CRN 17741-60-5

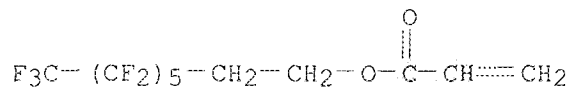
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CM 6

CRN 17527-29-6

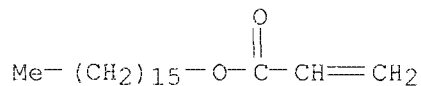
CMF C11 H7 F13 O2



CM 7

CRN 13402-02-3

CMF C19 H36 O2



L76 ANSWER 8 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1999:748617 HCAPLUS

DN 131:355925

TI Cosmetics containing fluoro compound-treated powders and fluoropolymers

IN Tokunaga, Tadayuki; Nanbu, Hiromi

PA Kao Corp., Japan

SO Jpn. Kokai Tokkyo Koho, 10 pp.

CODEN: JKXXAF

DT **Patent**

LA Japanese

FAN.CNT 1

PATENT NO.

KIND

DATE

APPLICATION NO.

DATE

17 july 2008

PI JP 11322543 A 19991124 JP 1998-125814 19980508 <--
 JP 3766541 B2 20060412
 PRAI JP 1998-125814 19980508 <--

AB Title cosmetics, which show water, oil, and wear resistance, film flexibility, durability, and stability, contain (A) powders treated with F-containing compds. and (B) film-forming (co)polymers of F-containing monomers.

A foundation was prepared from (C₆F₁₃CH₂CH₂O)2P(O)OH-treated pigments (TiO₂ 6, sericite 8, and Fe oxide 1.2 weight%), octamethylcyclotetrasiloxane 20, KF 96A (di-Me polysiloxane) 4, fluoropolymer [prepared from Fluowet MAE 600 [2-(perfluorooctyl)ethyl methacrylate] 40, stearyl methacrylate 56, and FM 711 (dimethylpolysiloxoxypropyl methacrylate) 4 g] 5, di-Me polysiloxane-polyoxyalkylene copolymer 2, glycerin 2, EtOH 15, perfume, and H₂O to 100 weight%.

IT 223736-96-7P

RL: BUU (Biological use, unclassified); SPN (Synthetic preparation); BIOL (Biological study); PREP (Preparation); USES (Uses)
 (cosmetics containing fluoro compound-treated powders and fluoropolymers)

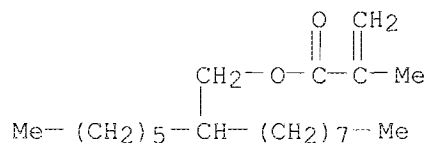
RN 223736-96-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, docosyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-methyl-2-propenoate and 2-hexyldecyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 215023-12-4

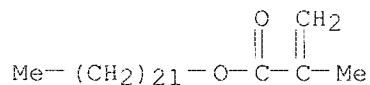
CMF C20 H38 O2



CM 2

CRN 16669-27-5

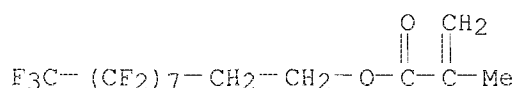
CMF C26 H50 O2



CM 3

CRN 1996-88-9

CMF C14 H9 F17 O2



L76 ANSWER 9 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1999:236489 HCAPLUS

DN 130:329045

TI Film-forming agents containing dimethyl polysiloxanes and fluoropolymers, and cosmetics containing them

IN Nanbu, Hiromi; Tanaka, Kimitaka; Nakano, Yukihiro

PA Kao Corp., Japan

SO Jpn. Kokai Tokkyo Koho, 15 pp.

CODEN: JKXXAF

DT **Patent**

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 11100306	A	19990413	JP 1997-262358	19970926 <--
	JP 3592903	B2	20041124		
	JP 2004107673	A	20040408	JP 2003-337064	20030929 <--
PRAI	JP 1997-262358	A3	19970926	<--	

AB Cosmetics, which show resistance to sweat, sebum, and mech. abrasion, contain title agents containing (a) linear or cyclic di-Me polysiloxanes showing b.p. at 101.3 kPa $\leq 280^\circ$ and viscosity at 25° 0.5-10 mm²/s and (b) fluoropolymers, which can be dissolved or dispersed into the di-Me polysiloxanes at 25° on mixing at 1/9 weight parts. Fluowet MAE 600 (CH₂:CMeCO₂C₂H₄C₈F₁₇) 40, stearyl methacrylate 56, and FM 711 (dimethylpolysiloxoxypropyl methacrylate) 4 g were polymerized in the presence of 2,2-azobis-2,4-dimethylvaleronitrile in PhMe at room temperature to 75° for 6.5 h to give 95.2 g copolymer showing good solubility in SH 244 (octamethylcyclotetrasiloxane), water contact angle 106° , and squalane contact angle 71° . A foundation containing the copolymer and di-Me polysiloxane was formulated.

IT 223736-96-7P

RL: BUU (Biological use, unclassified); PRP (Properties); SPN (Synthetic preparation); BIOL (Biological study); PREP (Preparation); USES (Uses) (cosmetics containing di-Me polysiloxanes and fluoropolymers as film-forming agents)

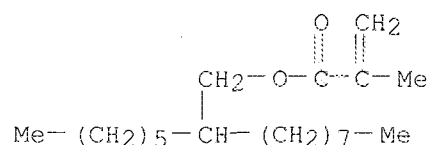
RN 223736-96-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, docosyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-methyl-2-propenoate and 2-hexyldecyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME).

CM 1

CRN 215023-12-4

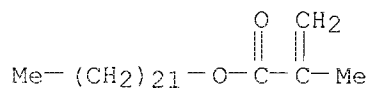
CMF C20 H38 O2



CM 2

CRN 16669-27-5

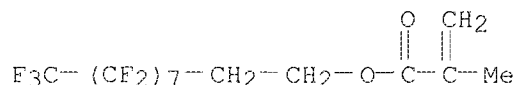
CMF C26 H50 O2



CM 3

CRN 1996-88-9

CMF C14 H9 F17 O2



L76 ANSWER 10 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1998:804146 HCAPLUS

DN 130:56998

TI Copolymers for cosmetics

IN Morita, Masamichi; Kubo, Motonobu

PA Daikin Industries Ltd., Japan

SO PCT Int. Appl., 76 pp.

CODEN: PIXXD2

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9855078	A1	19981210	WO 1998-JP2268	19980525 <--
	W: JP, US				
	RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
	EP 1000602	A1	20000517	EP 1998-921780	19980525 <--
	R: FR, GB, IT				
	US 6500439	B1	20021231	US 1999-445243	19991203 <--
PRAI	JP 1997-146284	A	19970604	<--	
	JP 1997-183529	A	19970709	<--	
	WO 1998-JP2268	W	19980525	<--	

OS MARPAT 130:56998

AB Copolymers for cosmetics, are obtained by polymerizing (A) 5-95 % of a fluoro(meth)acrylate with (B) 5-95 % of at least one fluorine-free monomer selected from the group consisting of silicone macromonomers, polyalkylene glycol (meth)acrylates, alkyl (meth)acrylates, and alkyl (meth)acrylate macromonomers. These copolymers can be easily incorporated into cosmetic prepsns. and form films excellent in water resistance, water repellency, oil repellency, feeling realized by using it and safety. These copolymers are capable of overcoming defects of powders treated with fluorine compds. CH₂:CHCO₂(CH₂)₂(CF₂CF₂)_nCF₂CF₃ (n = 3-5) was copolymd. with macromonomer Silaplane FM-0721 and solubilized in a cyclosiloxane. A powder foundation

contained the above product 10, a fluoro compound-treated powder mixture 89.8, parabens 0.1, and perfumes 0.1 %.

IT 217094-37-6P

RL: BUU (Biological use, unclassified); IMF (Industrial manufacture); BIOL (Biological study); PREP (Preparation); USES (Uses)
(fluoro(meth)acrylate copolymers for cosmetics)

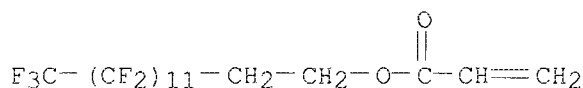
RN 217094-37-6 HCAPLUS

CN 2-Propenoic acid, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,12-heneicosafuorododecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate, octadecyl 2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,13,14,14,14-pentacosafuorotetradecyl 2-propenoate, block (9CI) (CA INDEX NAME)

CM 1

CRN 34395-24-9

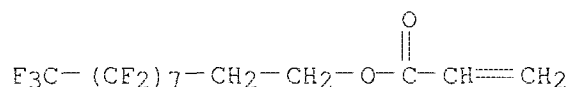
CMF C17 H7 F25 O2



CM 2

CRN 27905-45-9

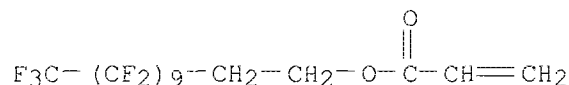
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CM 3

CRN 17741-60-5

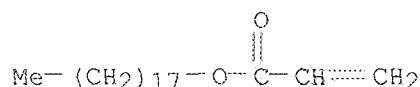
CMF C15 H7 F21 O2



CM 4

CRN 4813-57-4

CMF C21 H40 O2



RETABLE

Referenced Author (RAU)	Year (RPY)	VOL (RVL)	PG (RPG)	Referenced Work (RWK)	Referenced File
Daikin Industries Ltd				EP 263514 A	HCAPLUS
Daikin Industries Ltd				US 4587165 A	HCAPLUS
Daikin Industries Ltd				US 4810766 A	HCAPLUS
Daikin Industries Ltd				US 5614123 A1	HCAPLUS
Daikin Industries Ltd				JP 5890524 A	
Daikin Industries Ltd				EP 682146 A1	HCAPLUS
Daikin Industries Ltd				EP 79590 A	HCAPLUS
Daikin Industries Ltd				WO 9323442 A1	HCAPLUS
Daikin Industries Ltd				WO 9418377 A1	HCAPLUS
Daikin Industries Ltd	1983			JP 5883011 A	
Daikin Industries Ltd	1988			JP 6395207 A	
Daikin Industries Ltd	1994			JP 06228534 A	HCAPLUS
Daikin Industries Ltd	1994			JP 625361 A	
Daikin Industries Ltd	1997			JP 912428 A	
Minnesota Mining And Ma				CA 2021580 A	HCAPLUS
Minnesota Mining And Ma				EP 412771 A	HCAPLUS
Minnesota Mining And Ma				US 4972037 A	HCAPLUS
Minnesota Mining And Ma				AU 9050894 A	
Minnesota Mining And Ma				AU 9352107 A	HCAPLUS
Minnesota Mining And Ma	1991			JP 376713 A	
Nok Corp	1993			JP 05117333 A	HCAPLUS

L76 ANSWER 11 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1998:599698 HCAPLUS

DN 129:261709

OREF 129:53313a,53316a

TI Water- and oil-repellent compositions for textiles

IN Yamana, Masayuki; Uesugi, Norimasa

PA Daikin Industries, Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 7 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 10245783	A	19980914	JP 1997-40493	19970225 <--
	JP 3941146	B2	20070704		
PRAI	JP 1997-40493		19970225 <--		

AB Title comps., which give durable water and oil repellency and soft feel to textiles, comprise (A) silicone compds. $R_3SiO(R_2SiO)_l(RXSiO)_m(RYSiO)_n(R_2SiO)_oSiR_3$ (I), wherein X = an alkoxy-containing group, Y = an organic group having compatibility, R = a C1-20 hydrocarbon group, l, m, n, o = an integer of ≥ 1 , and $l + m + n + o \geq 10$ and (B) fluorine-containing copolymers obtained from polyfluoroalkyl group-containing polymerizable monomers and other polymerizable monomers. Thus, a cotton fabric was immersed in a composition comprising 15% fluorine-containing copolymer perchloroethylene solution prepared from 68 g $CF_3CF_2(CF_2CF_2)_nCH_2CH_2OC(=O)CH_2$ (n = 3, 4, 5, 6) and 32 g stearyl acrylate 5, I (R = CH_3 , X = $(EtO)_3SiCH_2CH_2$, Y = $HOCH_2CH_2$, Z = $C_{16}H_{33}$) 0.5, and perchloroethylene 94.5 parts, and heat-treated giving good water and oil repellency before and after washing and softer feel than untreated fabric.

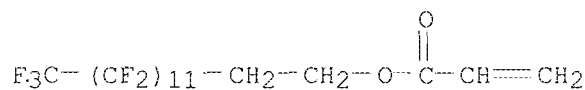
IT 213314-43-3P

RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (water- and oil-repellent comps. for textiles)

RN 213314-43-3 HCAPLUS
 CN 2-Propenoic acid, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,12-heneicosafuorododecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,13,14,14,15,15,16,16,16-nonacosafuorohexadecyl 2-propenoate, octadecyl 2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,13,14,14,14-pentacosafuorotetradecyl 2-propenoate (9CI)
 (CA INDEX NAME)

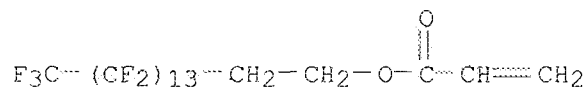
CM 1

CRN 34395-24-9
 CMF C17 H7 F25 O2



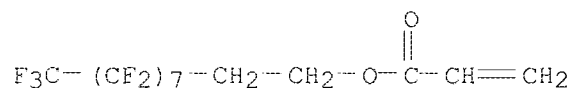
CM 2

CRN 34362-49-7
 CMF C19 H7 F29 O2



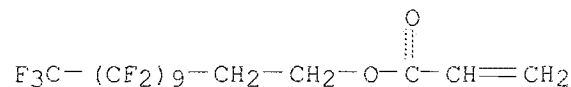
CM 3

CRN 27905-45-9
 CMF C13 H7 F17 O2



CM 4

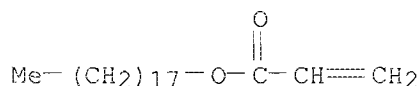
CRN 17741-60-5
 CMF C15 H7 F21 O2



CM 5

CRN 4813-57-4

CMF C21 H40 O2



L76 ANSWER 12 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1998:509232 HCAPLUS

DN 129:149848

OREF 129:30527a,30530a

TI Expandable thermoplastic resin beads and molded foam products made from the same

IN Sakoda, Yasuhiro; Takahashi, Hiroyuki; Sato, Masaya; Togo, Narihiko

PA Sekisui Kaseihin Kogyo K. K., Japan

SO PCT Int. Appl., 43 pp.

CODEN: PIXXD2

 DT **Patent**

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9831733	A1	19980723	WO 1998-JP41	19980108 <--
	W: AU, CA, CN, DE, GB, JP, SG, US				
	AU 9853422	A	19980807	AU 1998-53422	19980108 <--
	GB 2336552	A	19991027	GB 1999-17011	19980108 <--
	GB 2336552	B	20010328		
	JP 3523271	B2	20040426	JP 1998-534096	19980108 <--
	TW 495528	B	20020721	TW 1998-87100338	19980113 <--
PRAI	JP 1997-7981	A	19970120	<--	
	WO 1998-JP41	W	19980108	<--	

AB Resin beads are characterized in that the surfaces or skins of the beads are covered with or contain a fluorinated block copolymer comprising at least one segment of a fluorovinyl polymer derived from a fluorovinyl monomer and at least one segment which is an oleophilic vinyl polymer derived from an oleophilic vinyl monomer. Molded containers manufactured from these beads are suitable for oil-containing food.

 IT **210906-31-3P 210906-40-4P**

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(fluorine-containing block vinyl polymers coating for expandable thermoplastic resin beads)

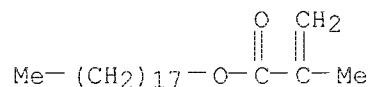
RN 210906-31-3 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, octadecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,9,10,10,10-hexadecafluoro-9-(trifluoromethyl)decyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 32360-05-7

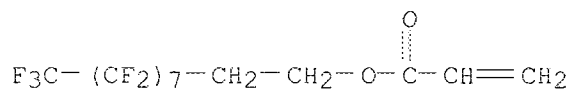
CMF C22 H42 O2



CM 2

CRN 27905-45-9

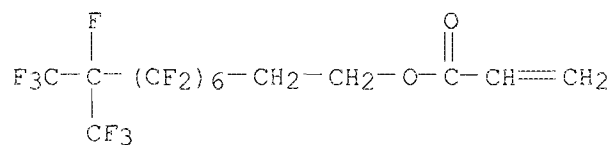
CMF C13 H7 F17 O2



CM 3

CRN 15577-26-1

CMF C14 H7 F19 O2



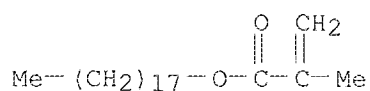
RN 210906-40-4 HCAPLUS

 CN 2-Propenoic acid, 2-methyl-, decyl ester, polymer with
 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and
 octadecyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 32360-05-7

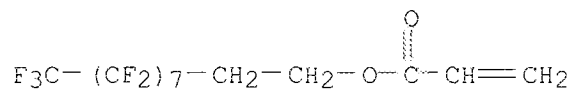
CMF C22 H42 O2



CM 2

CRN 27905-45-9

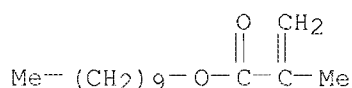
CMF C13 H7 F17 O2



CM 3

CRN 3179-47-3

CMF C14 H26 O2



RETABLE

Referenced Author (RAU)	Year (RPY)	VOL (RVL)	PG (RPG)	Referenced Work (RWK)	Referenced File
Hitachi Chemical Co Ltd	1991			JP 03190941 A	HCAPLUS
Hitachi Chemical Co Ltd	1993			JP 05140364 A	HCAPLUS
Sekisui Plastics Co Ltd	1987			GB 2185022	HCAPLUS
Sekisui Plastics Co Ltd	1987			JP 62158730 A	HCAPLUS

L76 ANSWER 13 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1998:392419 HCAPLUS

DN 129:123896

OREF 129:25351a,25354a

TI Fluorine-containing block copolymers for use in the prevention of epoxy resin adhesion on lead terminals of semiconductor devices and the devices

IN Tasaka, Tomohisa; Amagai, Naoyuki

PA Nippon Oil and Fats Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 10 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 10158462	A	19980616	JP 1996-317999	19961128 <--
PRAI	JP 1996-317999		19961128 <--		

AB The copolymers are dissolved in F-containing solvents and used as surface coatings for repelling unwanted accidental epoxy resin deposition during processing and have segments derived from F-containing vinyl monomers and blocks derived from F-free vinyl monomers. Thus, polymerizing CF₃(CF₂)₇CH₂CH₂OCOCH:CH₂ in 1,1,2-trifluoro-1,2,2-trichloroethane (I) using [CO(CH₂)₆C(Et)H(CH₂)₉C(O)OO]₁₀ polymeric peroxide initiator gave a F-containing polymer bearing peroxide group, which was block copolymer with stearyl methacrylate to give a block copolymer. A solution of the block copolymer in I was prepared for use as repellent coating for protecting lead terminals of semiconductor devices.

IT **210171-71-4P**, 2-(Perfluorooctyl)ethyl acrylate-perfluorooctylmethyl acrylate-stearyl methacrylate block copolymer
210171-72-5P, 2-(Perfluorooctyl)ethyl acrylate-2-(perfluorooctyl)ethyl methacrylate-stearyl methacrylate block copolymer
 RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (fluorine-containing block copolymers for use in prevention of epoxy resin deposition on lead terminals of semiconductor devices)

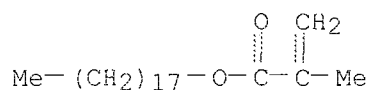
RN 210171-71-4 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, octadecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and 2,2,3,3,4,4,5,5,6,6,7,7,8,8,9,9-hexadecafluorononyl 2-propenoate, block (9CI) (CA INDEX NAME)

CM 1

CRN 32360-05-7

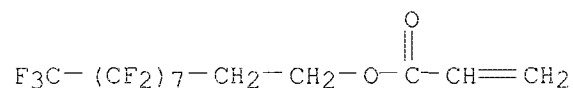
CMF C22 H42 O2



CM 2

CRN 27905-45-9

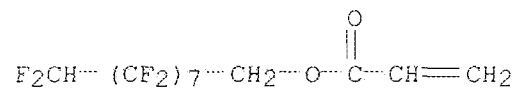
CMF C13 H7 F17 O2



CM 3

CRN 4180-26-1

CMF C12 H6 F16 O2



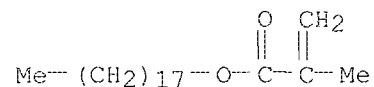
RN 210171-72-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-propenoate and octadecyl 2-methyl-2-propenoate, block (9CI) (CA INDEX NAME)

CM 1

CRN 32360-05-7

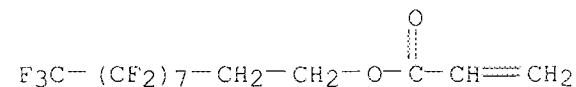
CMF C22 H42 O2



CM 2

CRN 27905-45-9

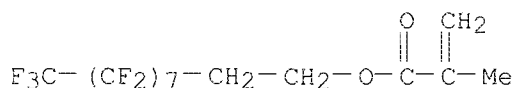
CMF C13 H7 F17 O2



CM 3

CRN 1996-88-9

CMF C14 H9 F17 O2



L76 ANSWER 14 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1998:286999 HCAPLUS

DN 129:55337

OREF 129:11517a,11520a

TI Thermoplastic elastomer compositions with good moldability for moldings with good tack-freeness, friction resistance, and water and oil repellency

IN Tanaka, Kazuyoshi; Yamada, Takeaki; Hashimoto, Yutaka

PA Dainippon Ink and Chemicals, Inc., Japan

SO Jpn. Kokai Tokkyo Koho, 16 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 10120910	A	19980512	JP 1996-279375	19961022 <--
PRAI	JP 1996-279375		19961022	<--	

AB The title compns. comprise thermoplastic elastomers and copolymers of RfXO2CCR:CH2 [Rf = C4-16 F-containing alkyl with or without ether linkage O; X = SO2NR'CH2CH2, CH2, CH2CH2, CH2CH(OH)CH2; R' = H, C1-3 alkyl; R = H, Me, C1, F, CN] and F-free (meth)acrylate monomer with C10-30 alkyl group. A copolymer was prepared from C8F17CH2CH2O2CCH:CH2 and stearyl acrylate, compounded (0.2%) with Millastomer 5030N, and injection-molded.

IT 208597-73-3P

RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (thermoplastic elastomer compns. with good moldability for moldings with good tack-freeness, friction resistance, and water and oil repellency)

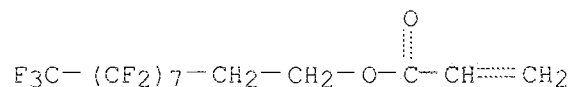
RN 208597-73-3 HCAPLUS

CN 2-Propenoic acid, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl ester, polymer with octadecyl 2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 27905-45-9

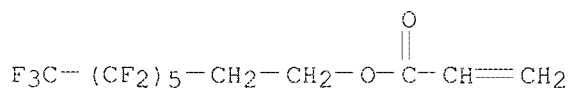
CMF C13 H7 F17 O2



CM 2

CRN 17527-29-6

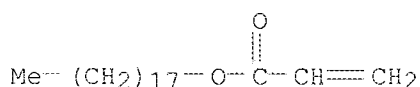
CMF C11 H7 F13 O2



CM 3

CRN 4813-57-4

CMF C21 H40 O2



L76 ANSWER 15 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1998:10595 HCAPLUS

DN 128:116253

OREF 128:22777a,22780a

TI Water- and oil-repellent compositions curable at room temperature and having low fluorine content

IN Fukushima, Noriyuki; Amagai, Naoyuki

PA Nippon Oil and Fats Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

 DT **Patent**

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 09328677	A	19971222	JP 1996-149578	19960611 <--
	JP 3800672	B2	20060726		
PRAI	JP 1996-149578		19960611 <--		

AB The title compns. useful for textile finishing contain C6-20 aliphatic hydrocarbon solvents and block copolymers of a polymer segment formed from fluoroalkyl monomer and alkyl (meth)acrylate (homopolymer Tg $\leq 20^\circ$) and an alkyl (meth)acrylate polymer segment. Stearyl methacrylate was polymerized in the presence of $[\text{CO}(\text{CH}_2)_6\text{CHEt}(\text{CH}_2)_9\text{C}(\text{O})\text{OO}]_n$ to obtain a peroxide-bonded polymer which was then block copolymd. with $\text{CF}_3(\text{CF}_2)_7\text{CH}_2\text{CH}_2\text{O}_2\text{CCH}:\text{CH}_2$ and stearyl acrylate in NAS-3 to give a block copolymer. The above block copolymer was tested as a 1% solution in heptane.

IT 201278-85-5P

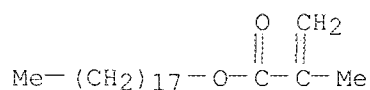
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(water- and oil-repellent compns. curable at room temperature and having low fluorine content)

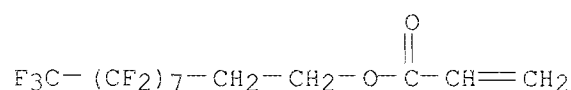
RN 201278-85-5 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, octadecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and octadecyl 2-propenoate (9CI) (CA INDEX NAME)

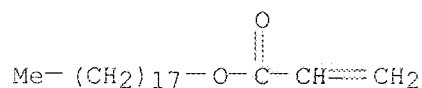
CM 1

 CRN 32360-05-7
 CMF C22 H42 O2


CM 2

 CRN 27905-45-9
 CMF C13 H7 F17 O2


CM 3

 CRN 4813-57-4
 CMF C21 H40 O2


L76 ANSWER 16 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1997:461414 HCAPLUS

DN 127:82875

OREF 127:15877a,15880a

TI Preparation of fluoropolymer solutions in fluoro hydrocarbons

IN Hashimoto, Yutaka; Tanaka, Kazuyoshi

PA Dainippon Ink and Chemicals, Inc., Japan

SO Jpn. Kokai Tokkyo Koho, 19 pp.

CODEN: JKXXAF

 DT **Patent**

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 09132606	A	19970520	JP 1995-292709	19951110 <--
	JP 3613855	B2	20050126		
PRAI	JP 1995-292709		19951110	<--	

AB The title solns., having good film-forming properties and giving films with good elec. insulating, water- and oil-repellent properties, are prepared by polymerization of monomers containing fluoroalkyl group-containing monomers,

and/or monomers containing no fluoroalkyl groups in fluoro solvents. The solns. are suitable for coating applications. Thus, radical polymerization of

90

17 july 2008

g C8F17CH2CH2O2CCH:CH2 with 10 g (CF3)2CHO2CCH:CH2 in 140 g perfluorooctane gave a transparent polymer (Mn 180,000) solution

IT 191750-93-3P

RL: IMF (Industrial manufacture); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(preparation of fluoropolymer solns. in fluoro hydrocarbons for coatings)

RN 191750-93-3 HCAPLUS

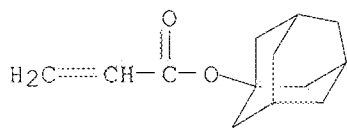
CN 2-Propenoic acid, dimethyltricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and 2,2,2-trifluoro-1-(trifluoromethyl)ethyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 146166-63-4

CMF C15 H22 O2

CCI IDS

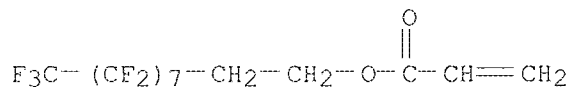


2 (D1-Me)

CM 2

CRN 27905-45-9

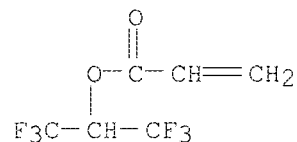
CMF C13 H7 F17 O2



CM 3

CRN 2160-89-6

CMF C6 H4 F6 O2



L76 ANSWER 17 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1996:391831 HCAPLUS

DN 125:60557

17 july 2008

OREF 125:11627a,11630a

TI Releasing agent, its cured coating, and plastic molding process using it
 IN Yamana, Masayuki; Nakamae, Yasushi; Sakashita, Hirotooshi; Kashiwagi, Masato

PA Daikin Industries Ltd., Japan

SO PCT Int. Appl., 43 pp.

CODEN: PIXXD2

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9612600	A1	19960502	WO 1995-JP2146	19951019 <--
	W: CN, KR, US				
	RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
	JP 08120178	A	19960514	JP 1994-256547	19941021 <--
	US 5804674	A	19980908	US 1997-809449	19970421 <--
PRAI	JP 1994-256547	A	19941021	<--	
	WO 1995-JP2146	W	19951019	<--	

AB The title agent, having long service life and can provide moldings with good surface finish without detriment to the fabricability, e.g., coatability or adhesiveness, comprises (a) alkoxy silane compound containing N:CRR1 group, (b) a Si- and/or F-containing compound having ≥ 2 OH or alkoxy groups, and (c) a perfluoroalkyl-containing (meth)acrylate polymer (e.g., 2-perfluorooctylethyl acrylate-stearyl acrylate copolymer).

IT 121018-93-7, 2-Ethylhexyl methacrylate-2-perfluorooctylethyl acrylate-stearyl acrylate copolymer

RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)

(releasing agent, its cured coating, and plastic molding process using it)

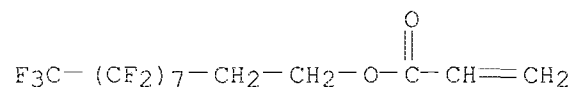
RN 121018-93-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-ethylhexyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and octadecyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 27905-45-9

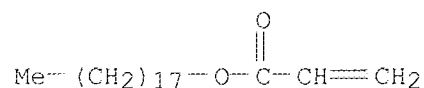
CMF C13 H7 F17 O2



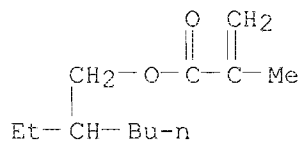
CM 2

CRN 4813-57-4

CMF C21 H40 O2



CM 3

CRN 688-84-6
CMF C12 H22 O2

L76 ANSWER 18 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1996:342202 HCAPLUS

DN 125:13246

OREF 125:2795a,2798a

TI Water- and oil-repellent stainproofer composition for textile finishing

IN Kubo, Motonobu; Morita, Masamichi; Ogisu, Hiroko; Enomoto, Takashi; Ueda, Akihiko

PA Daikin Industries Ltd., Japan

SO PCT Int. Appl., 32 pp.

CODEN: PIXXD2

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 9607709	A1	19960314	WO 1995-JP1648	19950821 <--
	W: US				
	RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
	JP 08073836	A	19960319	JP 1994-211105	19940905 <--
	JP 3399107	B2	20030421		
	EP 781825	A1	19970702	EP 1995-928624	19950821 <--
	EP 781825	B1	20031022		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LI, LU, MC, NL, PT, SE				
	AT 252624	T	20031115	AT 1995-928624	19950821 <--
	US 5883175	A	19990316	US 1997-812133	19970305 <--
PRAI	JP 1994-211105	A	19940905 <--		
	WO 1995-JP1648	W	19950821 <--		

AB The composition exhibiting good sedimentation stability contains as the essential ingredient a polymer emulsion prepared by dissolving a polyfluoroalkyl compound in ≥ 1 monomer of (meth)acrylates, vinyl esters, styrenic compds., vinyl chloride and vinylidene chloride, emulsifying the obtained solution in water, and polymerizing the oil-in-water emulsion. Preparing a copolymer (mol. weight 50,000) of $\text{CH}_2:\text{CHCO}_2(\text{CH}_2)_2(\text{CF}_2\text{CF}_2)_n\text{CF}_2\text{CF}_3$ ($n = 3, 4, 5$) and stearyl acrylate, dissolving the copolymer (20 g) in 40 g Et acrylate, stirring with water 150, Me_2CO 24, n-lauryl mercaptan 0.04, stearyltrimethylammonium chloride 1.8, and polyoxyethylene octylphenyl ether 4.2 g at 70° , and polymerizing with 0.2 g AIBN at 70 for 6 h gave a title emulsion.

IT 151809-72-2P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(water- and oil-repellent stainproofer composition for textile finishing)

RN 151809-72-2 HCAPLUS

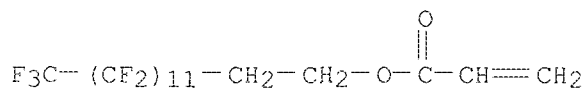
CN 2-Propenoic acid, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,12-heneicosafuorododecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate, octadecyl 2-propenoate and

3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,13,14,14,14-pentacosafuorotetradecyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 34395-24-9

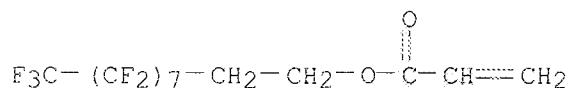
CMF C17 H7 F25 O2



CM 2

CRN 27905-45-9

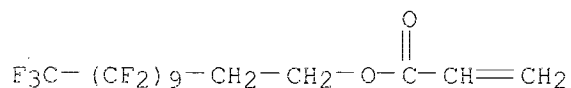
CMF C13 H7 F17 O2



CM 3

CRN 17741-60-5

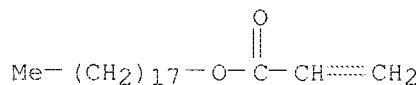
CMF C15 H7 F21 O2



CM 4

CRN 4813-57-4

CMF C21 H40 O2



L76 ANSWER 19 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1995:336577 HCAPLUS

DN 122:108610

OREF 122:20404h,20405a

TI Solvent-type water- and oil-repellent agents

IN Ito, Katsuji; Kamata, Takashi; Oomori, Juichi

PA Asahi Glass Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 4 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 06248257	A	19940906	JP 1993-59652	19930224 <--
	JP 3484716	B2	20040106		
PRAI	JP 1993-59652		19930224	<--	

AB The title agents contain aliphatic hydrocarbons optionally containing polar solvents, oil-soluble emulsifiers, and fluoro water- and oil-repellents. Thus, a water- and oil-repellent for nylon taffeta contained dimethylaminoethyl methacrylate-2-hydroxyethyl acrylate-perfluorononylethyl acrylate-stearyl acrylate copolymer, undecane, dipropylene glycol mono-Me ether, propylene glycol monostearate, and mineral spirit.

IT 160718-71-8P

RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)
(water- and oil-repellent agents containing fluoropolymers for nylon taffeta)

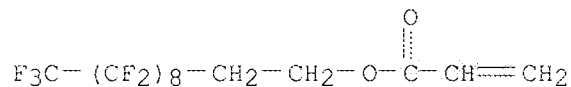
RN 160718-71-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-ethylhexyl ester, polymer with hexadecyl 2-methyl-2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,11-nonadecafluoroundecyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 41328-01-2

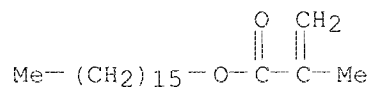
CMF C14 H7 F19 O2



CM 2

CRN 2495-27-4

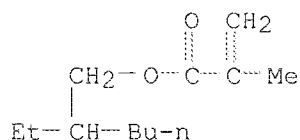
CMF C20 H38 O2



CM 3

CRN 688-84-6

CMF C12 H22 O2



L76 ANSWER 20 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1995:336574 HCAPLUS

DN 122:108609

OREF 122:20401a,20404a

TI Solvent-type fluorine-containing surface modifying agents

IN Ito, Katsuji; Kamata, Takashi

PA Asahi Glass Co Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 4 pp.

CODEN: JKXXAF

DT **Patent**

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 06248256	A	19940906	JP 1993-59651	19930224 <--
	JP 3601062	B2	20041215		
PRAI	JP 1993-59651		19930224	<--	

AB The title agents contain Cl-free F solvents. Thus, a water- and oil-repellent for nylon taffeta contained 2-ethylhexyl methacrylate-perfluorononylethyl acrylate-stearyl methacrylate copolymer, C6F14, and a diluent.

IT **160718-63-8P**

RL: IMF (Industrial manufacture); MOA (Modifier or additive use); PREP (Preparation); USES (Uses)

(water- and oil-repellents containing fluoro solvents for nylon taffeta)

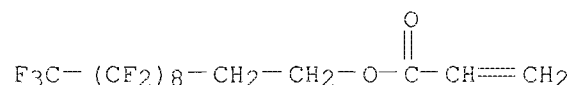
RN 160718-63-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-ethylhexyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,11-nonadecafluoroundecyl 2-propenoate and octadecyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 41328-01-2

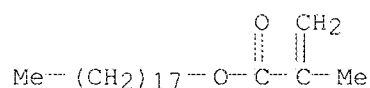
CMF C14 H7 F19 O2



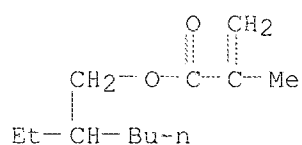
CM 2

CRN 32360-05-7

CMF C22 H42 O2



CM 3

 CRN 688-84-6
 CMF C12 H22 O2


L76 ANSWER 21 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1994:517358 HCAPLUS

DN 121:117358

OREF 121:21021a,21024a

TI Skin-cleansing compositions containing fluoropolymers and oily bases

IN Tsuda, Hiroko; Shigeta, Akira; Koyanagi, Hidenobu

PA Kao Corp, Japan

SO Jpn. Kokai Tokkyo Koho, 9 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 06048921	A	19940222	JP 1993-130768	19930601 <--
	US 5380455	A	19950110	US 1993-67790	19930527 <--
PRAI	JP 1992-140549	A1	19920601	<--	

AB Skin cleansers contain fluoropolymers having perfluoroalkyl group(s) and alkyl group(s) in the mols., and oily bases. The compns. are especially useful for cleansing F-containing makeup cosmetics on the skin. A cleanser contained stearyl methacrylate-perfluoroalkyl methacrylate copolymer 2, liquid paraffin 48, iso-Pr myristate 40, and polyoxyethylene glyceryl triisostearate 10 weight%.

IT 155734-07-9

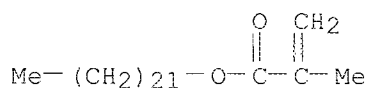
 RL: BIOL (Biological study)
 (skin cleansers containing oily bases and)

RN 155734-07-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, docosyl ester, polymer with dodecyl 2-methyl-2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

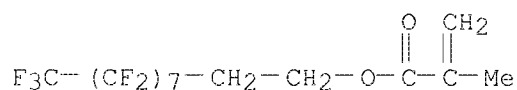
 CRN 16669-27-5
 CMF C26 H50 O2



CM 2

CRN 1996-88-9

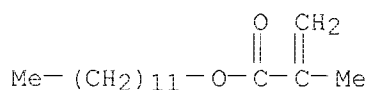
CMF C14 H9 F17 O2



CM 3

CRN 142-90-5

CMF C16 H30 O2



L76 ANSWER 22 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1994:10037 HCAPLUS

DN 120:10037

OREF 120:2137a,2140a

TI Release agents for molding of polyurethane foams

IN Yamana, Masayuki; Takubo, Seiji

PA Daikin Ind Ltd, Japan

SO Jpn. Kokai Tokkyo Koho, 10 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 05169460	A	19930709	JP 1991-336799	19911219 <--
	JP 3252419	B2	20020204		
PRAI	JP 1991-336799		19911219	<--	

AB Release agents having little migration to moldings contain 1-99% copolymers of 20-85% C1-20 polyfluoroalkyl (meth)acrylates with 15-80% C8-30 alkyl group-containing vinyl compds. and 1-99% waxes. Thus, a release agent contained 30:70 perfluorooctylethyl acrylate-stearyl acrylate copolymer 2, carnauba wax 2, and decane 96 parts.

IT 151809-72-2

RL: USES (Uses)

(release agents, containing waxes, for molding of polyurethane foams)

RN 151809-72-2 HCAPLUS

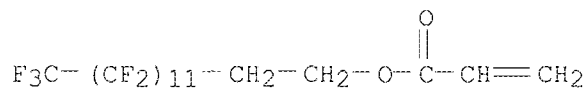
CN 2-Propenoic acid, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,12-heneicosafuorododecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate, octadecyl 2-propenoate and

3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,13,14,14,14-pentacosafuorotetradecyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 34395-24-9

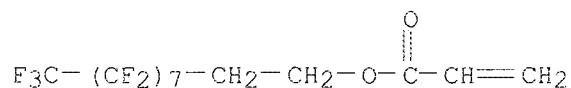
CMF C17 H7 F25 O2



CM 2

CRN 27905-45-9

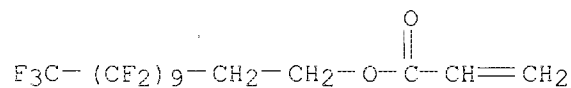
CMF C13 H7 F17 O2



CM 3

CRN 17741-60-5

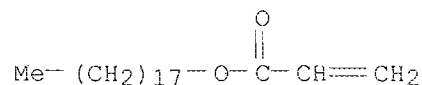
CMF C15 H7 F21 O2



CM 4

CRN 4813-57-4

CMF C21 H40 O2



L76 ANSWER 23 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1993:459752 HCAPLUS

DN 119:59752

OREF 119:10579a,10582a

TI Photosensitive composition for lithographic platemaking

IN Adachi, Yutaka; Nakai, Hideyuki; Tanaka, Takeshi

PA Konica Co., Japan

SO Jpn. Kokai Tokkyo Koho, 12 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 04335354	A	19921124	JP 1991-133353	19910510 <--
PRAI	JP 1991-133353		19910510	<--	

AB In the title photosensitive composition containing a F-containing surfactant, the

surfactant is a polymer incorporating fluoro-aliphatic group containing (meth)acrylates and polyoxyalkylene (meth)acrylates which have a C12-25 aliphatic hydrocarbon group at their ends. This photosensitive composition shows

good coating properties and firm layer adhesion.

IT 148740-63-0

RL: USES (Uses)

(surfactant, photosensitive composition containing, for lithog. platemaking)

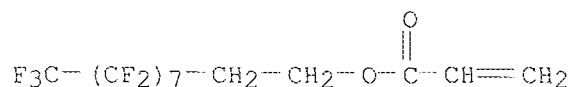
RN 148740-63-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,12-heneicosafluorododecyl 2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and tritetracontafluorotetracosenyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 27905-45-9

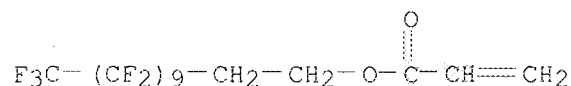
CMF C13 H7 F17 O2



CM 2

CRN 17741-60-5

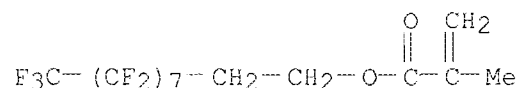
CMF C15 H7 F21 O2



CM 3

CRN 1996-88-9

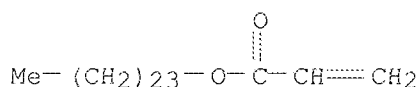
CMF C14 H9 F17 O2



CM 4

 CRN 148740-62-9
 CMF C27 H7 F43 O2
 CCI IDS

CM 5

 CRN 148740-61-8
 CMF C27 H9 F43 O2
 CCI IDS


43 (D1-F)

L76 ANSWER 24 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1989:518016 HCAPLUS

DN 111:118016

OREF 111:19757a,19760a

TI Copolymers useful as multifunctional additives in lubricants, and compositions containing these copolymers

IN Germanaud, Laurent; Azorin, Patrick; Lhopital, Michel; Truong Dinh Nguyen

PA Societe National Elf Aquitaine (SNEA), Fr.

SO Eur. Pat. Appl., 10 pp.

CODEN: EPXXDW

DT Patent

LA French

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 309317	A1	19890329	EP 1988-402315	19880914 <--
	EP 309317	B1	19920102		
	R: BE, DE, GB, IT, NL				
	FR 2620452	A1	19890317	FR 1987-12822	19870916 <--
	FR 2620452	B1	19911108		
	JP 01245005	A	19890929	JP 1988-231432	19880914 <--
PRAI	FR 1987-12822	A	19870916	<--	

AB The additives improve viscosity, wear, and dispersion characteristics. They are found by copolymg. an unsatd. monocarboxylic acid ester and ≥1 acrylic monomer containing F atoms and/or P and possibly N. A suitable copolymer is prepared from stearyl methacrylate, lauryl methacrylate, (perfluorooctyl)-2-Et methacrylate, dodecanethiol, and AIBN.

IT 122532-33-6

RL: USES (Uses)

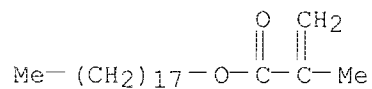
(lubricant multifunctional additive)

RN 122532-33-6 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, dodecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-methyl-2-propenoate and octadecyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

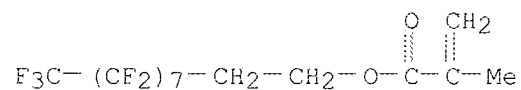
CM 1

CRN 32360-05-7
CMF C22 H42 O2



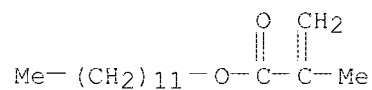
CM 2

CRN 1996-88-9
CMF C14 H9 F17 O2



CM 3

CRN 142-90-5
CMF C16 H30 O2



L76 ANSWER 25 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1989:516277 HCAPLUS

DN 111:116277

OREF 111:19503a,19506a

TI Transparent block copolymers of acrylate and unsaturated tricyclodecane derivatives with heat and impact resistance

IN Sugimori, Masahiro; Takeda, Haruko; Kato, Michiko

PA Mitsubishi Rayon Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 6 pp.

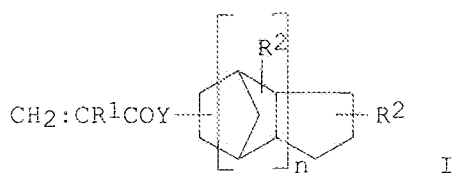
CODEN: JKXXAF

DT **Patent**

LA Japanese

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
-----	----	-----	-----	-----
PI JP 01004610	A	19890109	JP 1987-158823	19870627 <--
PRAI JP 1987-158823		19870627	<--	
GI				



AB Title copolymers are prepared which comprise terminal blocks from monomer mixts. containing $\geq 80\%$ tricyclodecane derivs. I ($\text{R}^1 = \text{H}, \text{Me}$; $\text{R}^2 = \text{H}, \text{halo}, \text{C1-3 alkyl}$; $\text{Y} = \text{O}, \text{OCH}_2\text{O}, \text{OCH}_2\text{CH}_2\text{O}$; $n = 1-4$) as well as 5-30% blocks (mol. weight 5000-60,000; glass temperature $\leq 40^\circ$) from monomer mixts. containing $\geq 80\%$ $\text{CH}_2:\text{CR}^3\text{CO}_2\text{R}^4$ [$\text{R}^3 = \text{H}, \text{Me}$; $\text{R}^4 = \text{C1-18 (fluoro)alkyl}, \text{CmH}_2\text{mSiX}_3, \text{CH}_2\text{CH}_2\text{OSiR}_5$; $\text{X} = \text{Me}, (\text{OSiMe}_2)_k\text{OSiMe}_3$; $\text{R}_5 = \text{C1-6 alkyl}$; $m = 2-5$; $k = 0-30$]. Thus, 500 g tricyclo[5.2.1.0^{2,6}]decyl methacrylate (II) was polymerized in the presence of trisdimethylaminosulfonium difluoride and [(2-methoxy-2-methyl-1-propenyl)oxy]trimethylsilane at $30-50^\circ$, 250 g lauryl methacrylate (III) was added and polymerized to give a block having mol. weight 10,000, and 500 g II was added and polymerized to give a block copolymer (IV; number-average mol. weight 50,000). IV was pelleted at 250° and injection molded to give a molding having heat distortion temperature 145° , Izod impact strength 7 kg-cm/cm, and light transmission 93%, vs. 70, 5, and 89, resp., for II-III random copolymer.

IT 122108-67-2P

RL: PREP (Preparation)

(preparation of transparent, heat- and impact-resistant)

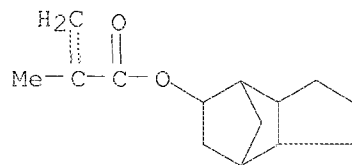
RN 122108-67-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, dodecyl ester, polymer with
 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl
 2-methyl-2-propenoate and octahydro-4,7-methano-1H-inden-5-yl
 2-methyl-2-propenoate, block (9CI) (CA INDEX NAME)

CM 1

CRN 34759-34-7

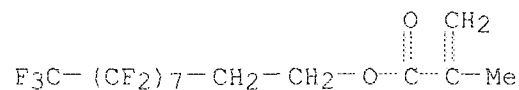
CMF C14 H20 O2



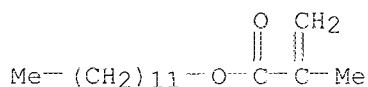
CM 2

CRN 1996-88-9

CMF C14 H9 F17 O2



CM 3

CRN 142-90-5
CMF C16 H30 O2

L76 ANSWER 26 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1989:408857 HCAPLUS

DN 111:8857

OREF 111:1661a,1664a

TI Fluoropolymers as oil and water repellents

IN Amimoto, Yoshio; Shinjo, Masayoshi; Enomoto, Takashi; Hayashi, Kazunori

PA Daikin Industries, Ltd., Japan

SO Eur. Pat. Appl., 11 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 294648	A2	19881214	EP 1988-108323	19880525 <--
	EP 294648	A3	19900418		
	EP 294648	B1	19930107		
	R: DE, FR, GB, NL				
	JP 01056711	A	19890303	JP 1988-127497	19880525 <--
	JP 07013118	B	19950215		
	US 5055538	A	19911008	US 1990-536073	19900611 <--
PRAI	JP 1987-128968	A	19870525	<--	
	US 1988-197917	B1	19880524	<--	

AB The title polymers, resistant to laundering and drycleaning and giving slip resistance to fabrics, contain monomers bearing C4-20 perfluoroalkyl groups 40-90, stearyl (meth)acrylate 5-50, and C2-8-alkyl (meth)acrylates 5-50%. A 60:32:2:3 CH₂:CHCO₂CH₂CH₂C₈F₁₇-stearyl acrylate-cyclohexyl methacrylate-glycidyl methacrylate copolymer emulsion, prepared by emulsion polymerization, was diluted to 12% nonvolatiles, applied to a polyester fabric, dried at 80°, and cured at 150° for 3 min to give a fabric with oil repellency (7 best, 0 worst) 5 and water repellency (100 best, 0 worst) 100+, vs. 2 and 100, resp., after laundering, and 2 and 80, resp., after drycleaning.

IT 121018-93-7

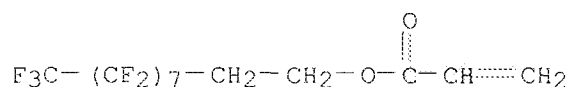
RL: TEM (Technical or engineered material use); USES (Uses)
(oil- and water-repellent finishes, for textiles)

RN 121018-93-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-ethylhexyl ester, polymer with
3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate and
octadecyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

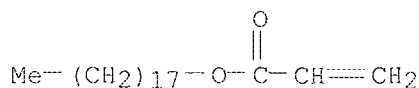
CRN 27905-45-9
CMF C13 H7 F17 O2



CM 2

CRN 4813-57-4

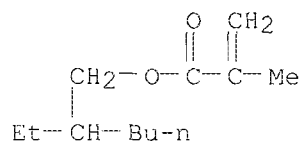
CMF C21 H40 O2



CM 3

CRN 688-84-6

CMF C12 H22 O2



L76 ANSWER 27 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1989:77027 HCAPLUS

DN 110:77027

OREF 110:12733a,12736a

TI Alicyclic hydrocarbyl methacrylate resins for exteriors of bilayered optical fibers

IN Yamamoto, Takashi; Matsumoto, Shiruyoshi; Murata, Ryuji; Uozu, Yoshihiro; Shimada, Katsuhiko

PA Mitsubishi Rayon Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 5 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 63180907	A	19880726	JP 1987-11224	19870122 <--
PRAI	JP 1987-11224		19870122	<--	

AB The optical fibers with good transparency and heat resistance are prepared from C>6 alicyclic hydrocarbyl methacrylate resin exteriors having refractive index (Ri) ≥0.01 lower than Ri of the interior resins. Thus, an optical fiber having PMMA interior (Ri 1.493) and tricyclo[5.2.1.0^{2,6}]deca-8-yl methacrylate-2,2,2-trifluoroethyl methacrylate-1,1,2,2-tetrahydroperfluorodecyl methacrylate-Me methacrylate copolymer exterior (Ri 1.414) showed a light transmission loss (Tl) 75 dB/km at 570 nm initially and 80 dB/km after heating at 100° for 24 h and flexural resistance (< 50% Tl after winding 10 times on a stick).

IT 118915-28-9

RL: USES (Uses)

(exteriors of bilayered optical fibers, flexible, heat-resistant)

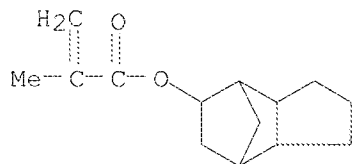
RN 118915-28-9 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl ester, polymer with octahydro-4,7-methano-1H-inden-5-yl 2-methyl-2-propenoate and 2,2,2-trifluoroethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 34759-34-7

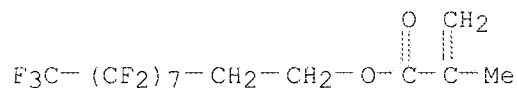
CMF C14 H20 O2



CM 2

CRN 1996-88-9

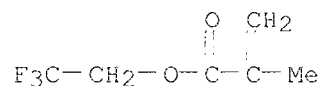
CMF C14 H9 F17 O2



CM 3

CRN 352-87-4

CMF C6 H7 F3 O2



L76 ANSWER 28 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1989:76705 HCAPLUS

DN 110:76705

OREF 110:12689a,12692a

TI Fluorine-containing resin composition having a low refractive index

IN Hashimoto, Yutaka; Kamei, Masayuki; Umaba, Toshihiko

PA Dainippon Ink Chemical Industry Co., Japan

SO Eur. Pat. Appl., 73 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 2

PATENT NO.

KIND

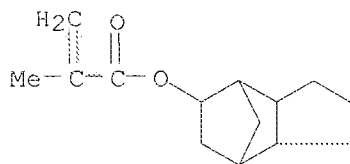
DATE

APPLICATION NO.

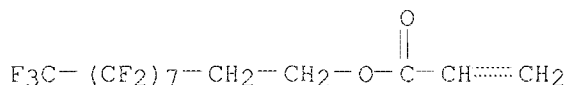
DATE

17 july 2008

PI -----
 EP 243605 A2 19871104 EP 1987-102644 19870225 <--
 EP 243605 A3 19890802
 EP 243605 B1 19930616
 R: DE, FR, GB
 JP 62199643 A 19870903 JP 1986-40383 19860227 <--
 JP 08011777 B 19960207
 JP 62250047 A 19871030 JP 1986-93226 19860424 <--
 JP 08019313 B 19960228
 JP 08211234 A 19960820 JP 1995-217391 19950825 <--
 JP 2570217 B2 19970108
 PRAI JP 1986-40383 A 19860227 <--
 JP 1986-93226 A 19860424 <--
 AB The title compns. for optical fibers, giving cured products having n
 ≤1.44, comprise F-containing (30%) polymers composed of F-containing
 (meth)acrylates, α,β-ethylenically unsatd. dicarboxylic acid
 esters, and/or mono(meth)acrylates, and polyfunctional monomer containing
 ≥2 (meth)acryloyl groups. Thus, a composition comprising 90:5:5
 CH₂:CHCO₂CH₂CH₂C₈F₁₇ (I)-Bu acrylate (II)-Bu fumarate copolymer 50, I 45,
 II 5, neopentyl glycol diacrylate 1, and 2-hydroxy-2-methyl-1-phenylpropan-
 1-one 4 parts had viscosity at 25° 8500 cP and n 1.362 and showed
 scratch-resistant adhesion to PMMA plate. A PMMA optical fiber core was
 coated with the above composition and UV-cured to give an optical fiber with
 transmission loss 1160 dB/km.
 IT **118629-47-3P 118650-56-9P**
 RL: PEP (Physical, engineering or chemical process); TEM (Technical or
 engineered material use); PREP (Preparation); PROC (Process); USES (Uses)
 (manufacture of, for UV-curable claddings for plastic and glass optical
 fibers)
 RN 118629-47-3 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, octahydro-4,7-methano-1H-inden-5-yl ester,
 polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl
 2-propenoate and exo-1,7,7-trimethylbicyclo[2.2.1]hept-2-yl
 2-methyl-2-propenoate (9CI) (CA INDEX NAME)
 CM 1
 CRN 34759-34-7
 CMF C14 H20 O2



CM 2
 CRN 27905-45-9
 CMF C13 H7 F17 O2

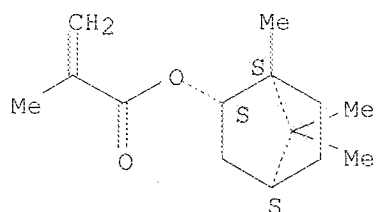


CM 3

CRN 7534-94-3

CMF C14 H22 O2

Relative stereochemistry.



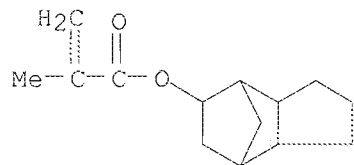
RN 118650-56-9 HCAPLUS

 CN 2-Propenoic acid, 2-methyl-, octahydro-4,7-methano-1H-inden-5-yl ester,
 polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl
 2-propenoate and exo-1,7,7-trimethylbicyclo[2.2.1]hept-2-yl 2-propenoate
 (9CI) (CA INDEX NAME)

CM 1

CRN 34759-34-7

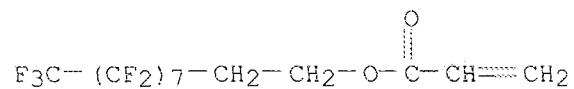
CMF C14 H20 O2



CM 2

CRN 27905-45-9

CMF C13 H7 F17 O2

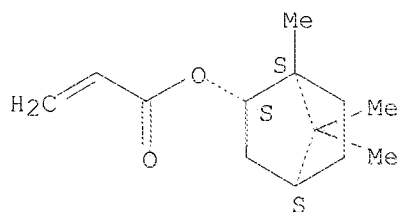


CM 3

CRN 5888-33-5

CMF C13 H20 O2

Relative stereochemistry.



L76 ANSWER 29 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1988:475157 HCAPLUS

DN 109:75157

OREF 109:12581a,12584a

TI Aerosol-type water- and oil-repellent agent compositions

IN Amimoto, Yoshio; Aoyama, Hiroichi; Okamoto, Sumiko

PA Daikin Industries, Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 5 pp.

CODEN: JKXXAF

DT **Patent**

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 63075082	A	19880405	JP 1986-221202	19860918 <--
	JP 04064636	B	19921015		
PRAI	JP 1986-221202		19860918	<--	

AB The title comps. contain (A) (co)polymers of compds. having perfluoroalkyl or perfluoroalkenyl groups and (meth)acrylic acid groups, (B) silicone oil, silicone varnish, or their mixts., (C) solvents, and (D) propellants with A-B ratio 30-95:5-70, A + B are 0.2-2.0% of A + B + C, and the ratio of D to A + B + C is 1:2-4. Thus, a composition containing copolymers of CF₃(CF₂)_nCH₂CH₂O₂CCH:CH₂ (n = 3-7) with 2-ethylhexyl methacrylate, Me chloroform, Toray SH700 (silicon), and Daiflon 12 (Cl₂CF₂) and was sprayed on a black nylon cloth without whitening.

IT 115708-20-8 115735-60-9

RL: USES (Uses)

(oil- and water-repellents, containing silicones, for textiles)

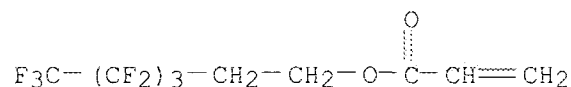
RN 115708-20-8 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-ethylhexyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate, 3,3,4,4,5,5,6,6,6-nonafluorohexyl 2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,9-pentadecafluorononyl 2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-propenoate and 3,3,4,4,5,5,6,6,7,7,7-undecafluoroheptyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 52591-27-2

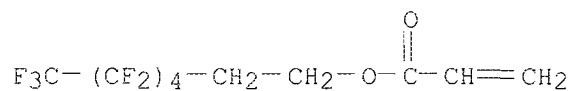
CMF C9 H7 F9 O2



CM 2

CRN 41327-99-5

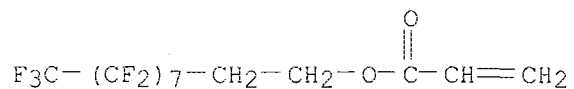
CMF C10 H7 F11 O2



CM 3

CRN 27905-45-9

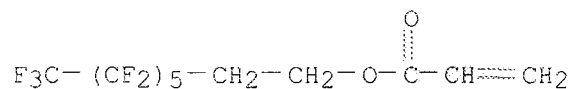
CMF C13 H7 F17 O2



CM 4

CRN 17527-29-6

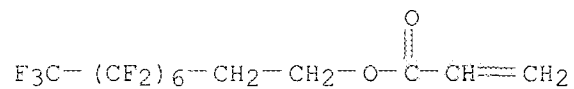
CMF C11 H7 F13 O2



CM 5

CRN 1799-55-9

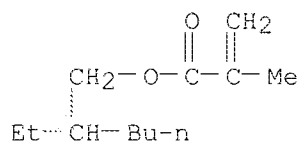
CMF C12 H7 F15 O2



CM 6

CRN 688-84-6

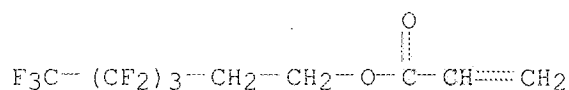
CMF C12 H22 O2



RN 115735-60-9 HCAPLUS
 CN 2-Propenoic acid, 2-methyl-, octadecyl ester, polymer with
 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate,
 3,3,4,4,5,5,6,6,6-nonafluorohexyl 2-propenoate,
 3,3,4,4,5,5,6,6,7,7,8,8,9,9,9-pentadecafluorononyl 2-propenoate,
 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-propenoate and
 3,3,4,4,5,5,6,6,7,7,7-undecafluoroheptyl 2-propenoate (9CI) (CA INDEX
 NAME)

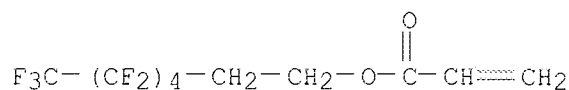
CM 1

CRN 52591-27-2
 CMF C9 H7 F9 O2



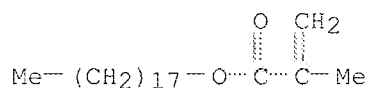
CM 2

CRN 41327-99-5
 CMF C10 H7 F11 O2



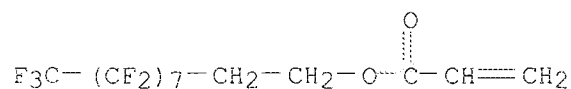
CM 3

CRN 32360-05-7
 CMF C22 H42 O2



CM 4

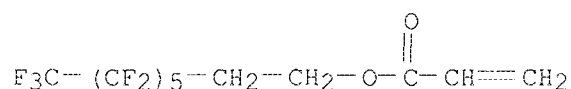
CRN 27905-45-9
 CMF C13 H7 F17 O2



CM 5

CRN 17527-29-6

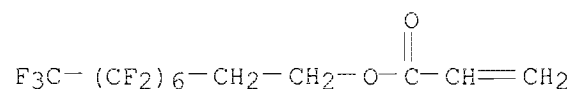
CMF C11 H7 F13 O2



CM 6

CRN 1799-55-9

CMF C12 H7 F15 O2



L76 ANSWER 30 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1987:6257 HCAPLUS

DN 106:6257

OREF 106:1143a,1146a

TI Surface-treated sulfur powder for vulcanizing

IN Komatsu, Sueyoshi; Urano, Naoyuki; Kato, Fumio

PA Asahi Glass Co., Ltd., Japan; Tsurumi Chemical Industrial Co., Ltd.

SO Jpn. Kokai Tokkyo Koho, 5 pp.

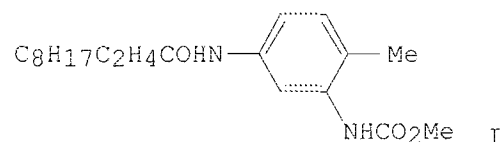
CODEN: JKXXAF

 DT **Patent**

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 61146702	A	19860704	JP 1984-268499	19841221 <--
PRAI	JP 1984-268499		19841221	<--	
GI					



AB Powdered S is surface treated with polyfluoroalkyl compound antistatic agents. Thus, powdered S was immersed in 1% (I) solution in $\text{CCl}_2\text{FCClF}_2$, filtered, and powdered to 200 mesh to give a product having fluidity excellent, initial electrostatic charge buildup 100 V, and pulsed treatment electrostatic charge buildup 100 V, compared with bad, 200, and 800, resp., for powdered S without I coating.

IT **105699-35-2**

RL: USES (Uses)

(antistatic agents, for powdered sulfur)

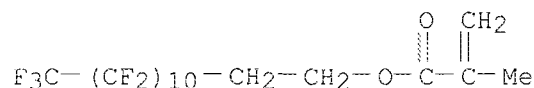
RN 105699-35-2 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,12-heneicosafuorododecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-methyl-2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,11-nonadecafluoroundecyl 2-methyl-2-propenoate, octadecyl 2-methyl-2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,13,14,14,14-pentacosafuorotetradecyl 2-methyl-2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,9-pentadecafluorononyl 2-methyl-2-propenoate, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,13,13-tricosafuorotridecyl 2-methyl-2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 51002-74-5

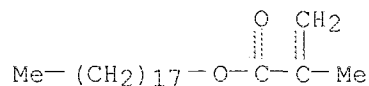
CMF C17 H9 F23 O2



CM 2

CRN 32360-05-7

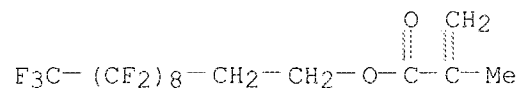
CMF C22 H42 O2



CM 3

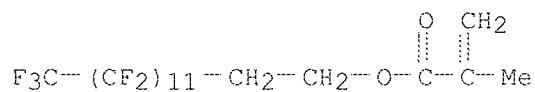
CRN 15899-09-9

CMF C15 H9 F19 O2



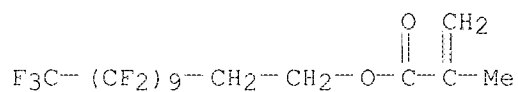
CM 4

CRN 6014-75-1
CMF C18 H9 F25 O2



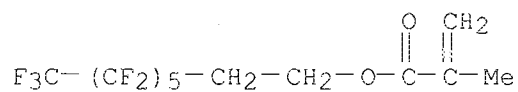
CM 5

CRN 2144-54-9
CMF C16 H9 F21 O2



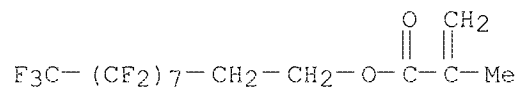
CM 6

CRN 2144-53-8
CMF C12 H9 F13 O2



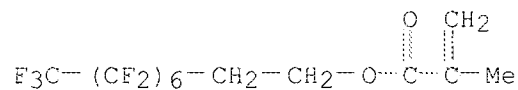
CM 7

CRN 1996-88-9
CMF C14 H9 F17 O2



CM 8

CRN 1815-18-5
CMF C13 H9 F15 O2



L76 ANSWER 31 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN
AN 1984:8457 HCAPLUS

17 july 2008

DT Patent
LA Japanese
FAN.CNT 1

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 58103550	A	19830620	JP 1981-202024	19811214 <--
	JP 63037832	B	19880727		
PRAI	JP 1981-202024		19811214	<--	

AB The title repellent contains -O₂CZCO- (Z = cyclic acid anhydride residual group without -COOCO-) and -OCH[(CH₂)_nR]CH₂- or -CH[(CH₂)_nR]CH₂O- (R = C₃-21 perfluoroalkyl; n = 0, 1), optionally -(OCR₁R₂CR₃R₄), (R₁-4 = H, alkyl or substituted alkyl, aryl or substituted aryl, resp.) and/or -[N(COR₅)(CH₂)_m]- (R₅ = H, alkyl, aryl; m = 2 or 3) and a homopolymer of an acrylic ester or methacrylic ester containing C₃-21 perfluoroalkyl or a copolymer containing ≥70 weight% of these F-containing esters. The repellent exhibits excellent anti-staining and oil- and water-repelling properties in textile treatment. Thus, the F-containing ester [69725-49-1] prepared by treating (CF₃)₂CF(CF₂CF₂)₃R₆ (R₆ = glycidyl), phthalic anhydride, and N,N-dimethylbenzylamine was mixed with a F-containing acrylic polymer [79062-81-0] prepared by treating (CF₃)₂CF(CF₂CF₂)_nCH₂CH₂OCOCH:CH₂ (weight ratio 4:2:1 mixture of the compds. n = 3, 4, 5, resp.) and stearyl acrylate in the presence of Cation AB and Nonion NS-220, acetone, ethylene glycol, and AIBN amidine HCl to give the title repellent for nylon taffeta.

IT 79062-81-0

RL: USES (Uses)

(oilproofing and waterproofing agents, for textiles)

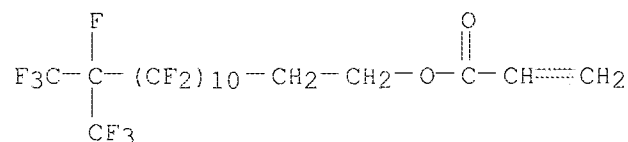
RN 79062-81-0 HCAPLUS

CN 2-Propenoic acid, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,12,12,12-eicosafuoro-11-(trifluoromethyl)dodecyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,10,10,10-hexadecafluoro-9-(trifluoromethyl)decyl 2-propenoate, octadecyl 2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,11,12,12,13,14,14,14-tetracosafuoro-13-(trifluoromethyl)tetradecyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 52956-82-8

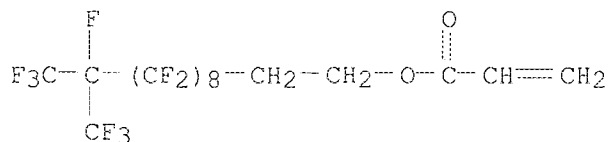
CMF C18 H7 F27 O2



CM 2

CRN 52956-81-7

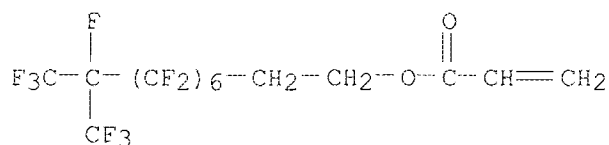
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CM 3

CRN 15577-26-1

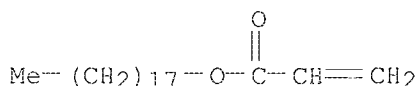
CMF C14 H7 F19 O2



CM 4

CRN 4813-57-4

CMF C21 H40 O2



L76 ANSWER 32 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1981:516632 HCAPLUS

DN 95:116632

OREF 95:19591a,19594a

TI Preventing adhesion of epoxy potting compounds on lead wires

PA Daikin Kogyo Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 7 pp.

CODEN: JKXXAF

 DT **Patent**

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 56053116	A	19810512	JP 1979-129046	19791005 <--
	JP 62029473	B	19870626		
PRAI	JP 1979-129046	A	19791005	<--	

AB Compns. preventing adhesion of epoxy potting compds. on lead wires of elec. components to be potted contain 40-90:60-10 copolymers of C4-21 perfluoroalkyl group-containing monomers and C12-18 alkyl (meth)acrylates. For example, a solution from (CF₃)₂CF(CF₂)_nCH₂CH₂O₂CCH:CH₂ (n = 6, 8, 10 in 4:3:1 ratio) 25.6, stearyl acrylate 6.4, and MeCHCl₃ 200 g was treated with 0.3 g tert-Bu perpivalate (as 70% solution in paraffin) at 55° for 7 h and then with 0.3 g tert-Bu perpivalate at 55° for 7 h to give a solution which was dip-coated on condenser lead wire to prevent adhesion of epoxy potting compound

IT 79062-81-0

RL: USES (Uses)

(adhesion prevention by, of epoxy potting compds. on lead wires)

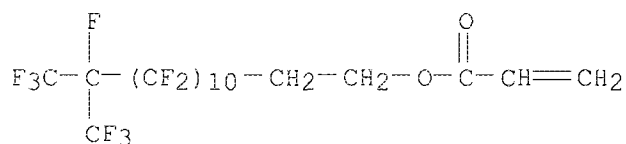
RN 79062-81-0 HCAPLUS

CN 2-Propenoic acid, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,11,12,12,12-
 eicosafluoro-11-(trifluoromethyl)dodecyl ester, polymer with
 3,3,4,4,5,5,6,6,7,7,8,8,9,10,10,10-hexadecafluoro-9-(trifluoromethyl)decyl
 2-propenoate, octadecyl 2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,
 11,11,12,12,13,14,14,14-tetracosafuoro-13-(trifluoromethyl)tetradecyl
 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 52956-82-8

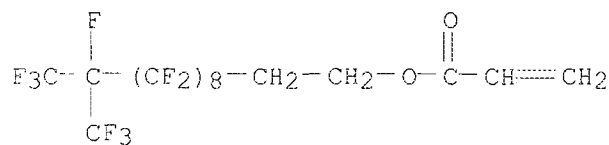
CMF C18 H7 F27 O2



CM 2

CRN 52956-81-7

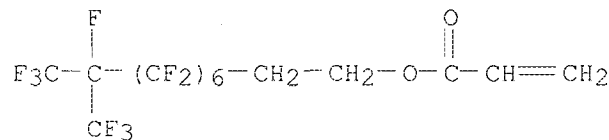
CMF C16 H7 F23 O2



CM 3

CRN 15577-26-1

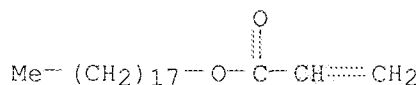
CMF C14 H7 F19 O2



CM 4

CRN 4813-57-4

CMF C21 H40 O2



L76 ANSWER 33 OF 33 HCAPLUS COPYRIGHT 2008 ACS on STN

AN 1976:24435 HCAPLUS

DN 84:24435

OREF 84:3971a,3974a

TI Dry planographic printing plate

IN Cords, Donald P.

PA du Pont de Nemours, E. I., and Co., USA

SO U.S., 14 pp.

CODEN: USXXAM

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 3910187	A	19751007	US 1973-390372	19730822 <--
PRAI	US 1971-176094	A2	19710830	<--	

AB Fluorinated compds. having a fluorinated radical at one end and the polar. Radical at the other end and F-containing polymers having a fluorinated radical linked to a radical having a polymerizable C-to-C linkage are ink-repellent and are used in the preparation of lithog. plates. Thus, a brushed and smooth Cu plate was spray coated with a 10% solution of a mixture of 95 parts CF₃(CF₂)₅CH₂CH₂OCOCH:CH₂ and 5 parts of benzoin methyl ether in 1,1,2-trichloro-1,2,2-trifluoroethane to give a dry layer of 0.0025 cm thick, exposed through a stencil to light from a G. E. Blacklite fluorescent tube at a distance of 5 in and for 1 min, heated to 150-175° until the monomer ceased to vaporize, and when contacted with printing ink accepted ink only in the nonexposed areas.

IT 57678-89-4

RL: USES (Uses)

(lithog. plate coating composition, ink-repellent)

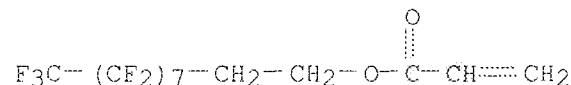
RN 57678-89-4 HCAPLUS

CN 2-propenoic acid, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl ester, polymer with octyl 2-propenoate and 3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 27905-45-9

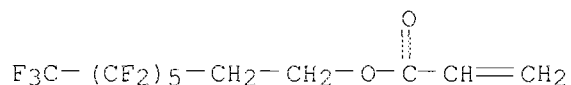
CMF C13 H7 F17 O2



CM 2

CRN 17527-29-6

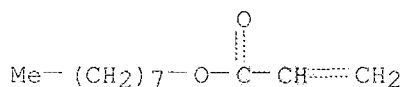
CMF C11 H7 F13 O2



CM 3

CRN 2499-59-4

CMF C11 H20 O2



=> fil reg

FILE 'REGISTRY' ENTERED AT 10:06:19 ON 17 JUL 2008

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STRUCTURE FILE UPDATES: 16 JUL 2008 HIGHEST RN 1034374-44-1

DICTIONARY FILE UPDATES: 16 JUL 2008 HIGHEST RN 1034374-44-1

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH January 9, 2008.

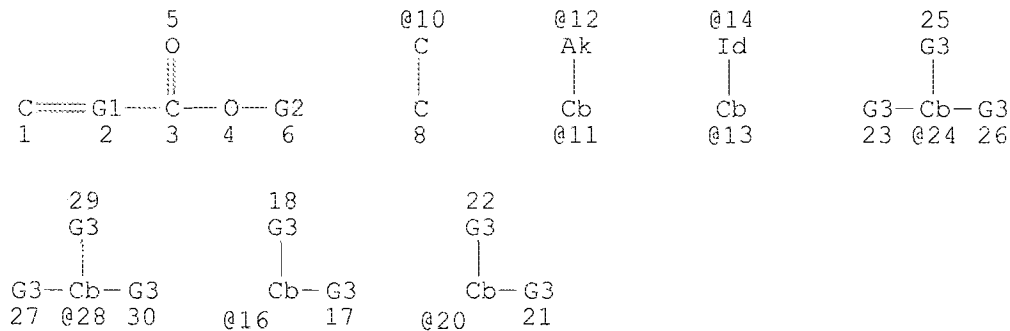
Please note that search-term pricing does apply when conducting SmartSELECT searches.

REGISTRY includes numerically searchable data for experimental and predicted properties as well as tags indicating availability of experimental property data in the original document. For information on property searching in REGISTRY, refer to:

<http://www.cas.org/support/stngen/stndoc/properties.html>

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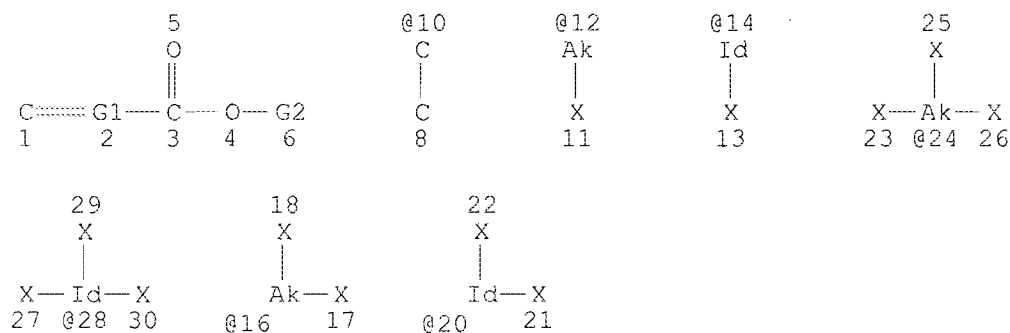
L14 STR



VAR G1=C/10
 VAR G2=AK/ID/CB/12/14/11/13/16/20/24/28
 VAR G3=AK/ID
 NODE ATTRIBUTES:
 CONNECT IS M1 RC AT 24
 CONNECT IS M1 RC AT 28
 DEFAULT MLEVEL IS ATOM
 DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
 RING(S) ARE ISOLATED OR EMBEDDED
 NUMBER OF NODES IS 26

STEREO ATTRIBUTES: NONE
 L15 SCR 2043
 L17 188039 SEA FILE=REGISTRY CSS FUL L14 AND L15
 L18 STR

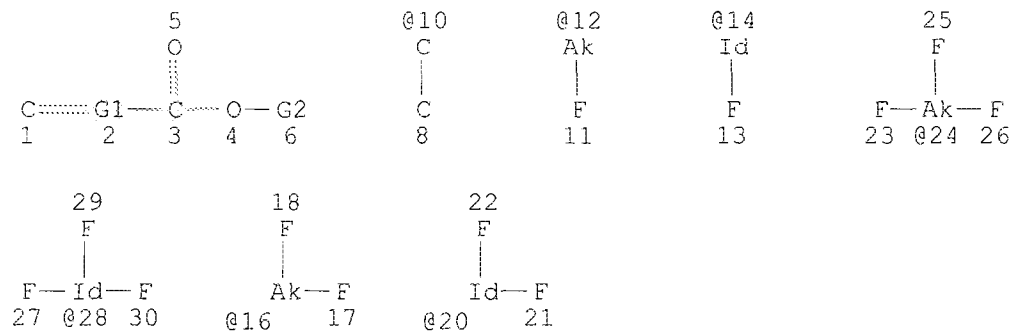


VAR G1=C/10
 VAR G2=12/14/16/20/24/28
 NODE ATTRIBUTES:
 CONNECT IS M1 RC AT 24
 CONNECT IS M1 RC AT 28
 DEFAULT MLEVEL IS ATOM
 DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
 RING(S) ARE ISOLATED OR EMBEDDED
 NUMBER OF NODES IS 26

STEREO ATTRIBUTES: NONE
 L20 6576 SEA FILE=REGISTRY SUB=L17 CSS FUL L18

L21 STR



VAR G1=C/10

VAR G2=12/14/16/20/24/28

NODE ATTRIBUTES:

CONNECT IS M1 RC AT 24

CONNECT IS M1 RC AT 28

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 26

STEREO ATTRIBUTES: NONE

L22 SCR 1992 OR 2016 OR 2021 OR 2026

L24 SCR 2068 OR 2070

L26 3070 SEA FILE=REGISTRY SUB=L20 CSS FUL L21 NOT (L22 OR L24)

L27 STR

Hy 1

NODE ATTRIBUTES:

DEFAULT MLEVEL IS ATOM

DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

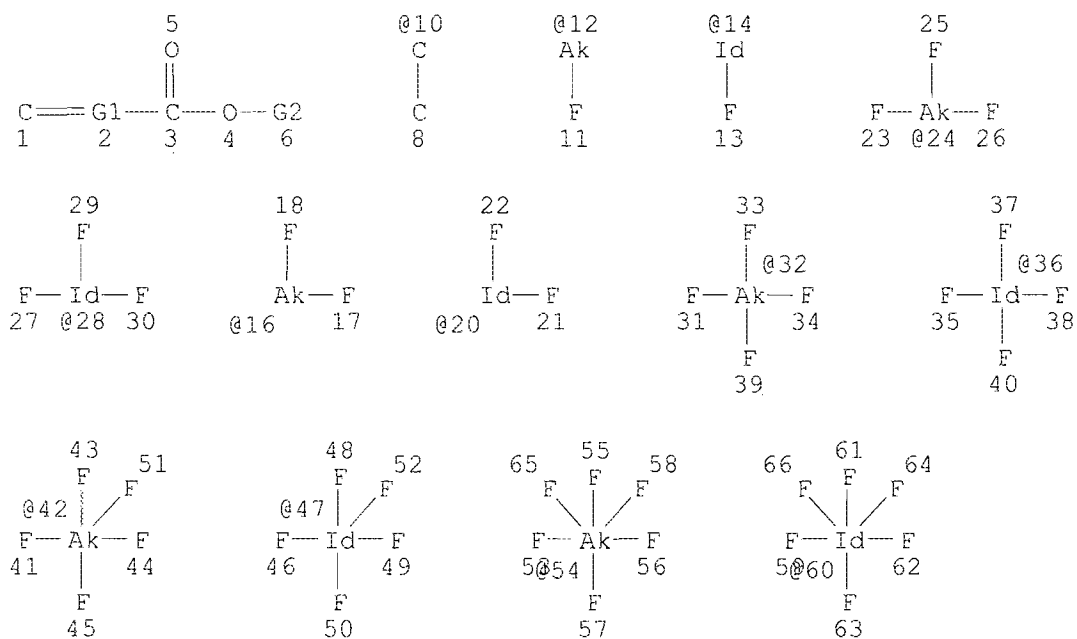
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STEREO ATTRIBUTES: NONE

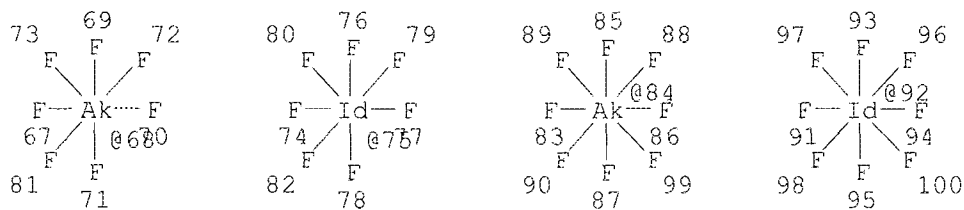
L29 621 SEA FILE=REGISTRY SUB=L26 SSS FUL L27

L30 2449 SEA FILE=REGISTRY ABB=ON PLU=ON L26 NOT L29

L31 STR



Page 1-A

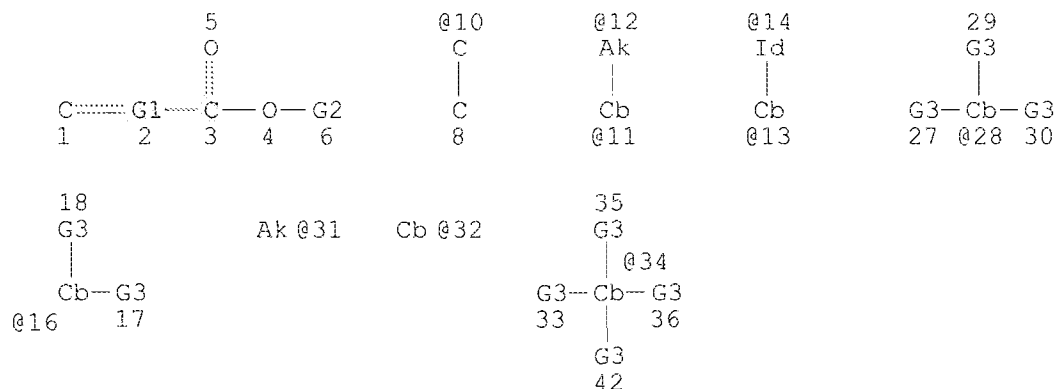


Page 2-A

VAR G1=C/10
 VAR G2=12/14/16/20/24/28/32/36/42/47/54/60/68/75/84/92
 NODE ATTRIBUTES:
 CONNECT IS M1 RC AT 84
 CONNECT IS M1 RC AT 92
 DEFAULT MLEVEL IS ATOM
 DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
 RING(S) ARE ISOLATED OR EMBEDDED
 NUMBER OF NODES IS 96

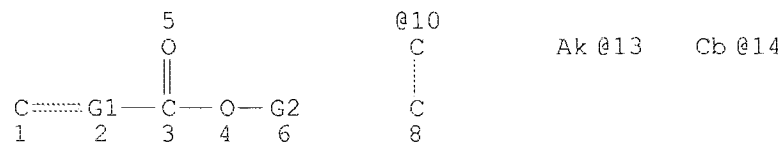
STEREO ATTRIBUTES: NONE
 L33 2360 SEA FILE=REGISTRY SUB=L30 CSS FUL L31
 L34 STR



VAR G1=C/10
 VAR G2=31/32/ID/12/14/11/13/16/28/34
 VAR G3=AK/ID
 NODE ATTRIBUTES:
 CONNECT IS M1 RC AT 34
 DEFAULT MLEVEL IS ATOM
 GGCAT IS HIC AT 31
 DEFAULT ECLEVEL IS LIMITED
 ECOUNT IS M7 C AT 32

GRAPH ATTRIBUTES:
 RING(S) ARE ISOLATED OR EMBEDDED
 NUMBER OF NODES IS 26

STEREO ATTRIBUTES: NONE
 L36 942 SEA FILE=REGISTRY SUB=L33 CSS FUL L34
 L39 887 SEA FILE=REGISTRY ABB=ON PLU=ON L36 NOT (C8H8 OR C10H10)
 L40 643 SEA FILE=REGISTRY ABB=ON PLU=ON L39 AND NC>=3
 L41 622 SEA FILE=REGISTRY ABB=ON PLU=ON L40 NOT UNSPECIFIED
 L42 476 SEA FILE=REGISTRY ABB=ON PLU=ON L41 NOT (818-61-1 OR 79-10-7
 OR 79-41-4)/CRN
 L43 442 SEA FILE=REGISTRY ABB=ON PLU=ON L42 NOT 868-77-9/CRN
 L44 STR



VAR G1=C/10
 VAR G2=13/14/ID
 NODE ATTRIBUTES:
 DEFAULT MLEVEL IS ATOM
 GGCAT IS LOC AT 13
 GGCAT IS LOC AT 14
 DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
 RING(S) ARE ISOLATED OR EMBEDDED
 NUMBER OF NODES IS 10

STEREO ATTRIBUTES: NONE

L46 197 SEA FILE=REGISTRY SUB=L43 CSS FUL L44

=> d his

(FILE 'HOME' ENTERED AT 09:12:24 ON 17 JUL 2008)
SET COST OFF

FILE 'HCAPLUS' ENTERED AT 09:12:53 ON 17 JUL 2008

L1 1 S US20060173148/PN OR (US2005-526381# OR WO2003-JP11301 OR JP20
E SASAKI/AU
L2 3 S E3
E SASAKI H/AU
L3 490 S E3
E SASAKI HIR/AU
L4 201 S E17
E SASAKI NAME/AU
L5 73 S E4
E HIROKI/AU
L6 2 S E3
E HIROKI S/AU
L7 21 S E3
E HIROKI NAME/AU
E NEMORI/AU
L8 65 S E7-E10
E RYOICHI/AU
L9 1 S E3
L10 163496 S FUJI?/CO, PA, CS
E FUJI/CO
E FUJI FILM/CO
E FUJIFILM/CO
E E10+ALL
E E1+ALL
L11 54516 S E2+RT OR E2-E96/PA, CS
E FUJI PHOTO/CO
E E9+ALL
L12 1 S L1 AND L2-L11
SEL RN

FILE 'REGISTRY' ENTERED AT 09:16:46 ON 17 JUL 2008

L13 13 S E1-E13
L14 STR
L15 SCR 2043
L16 50 S L14 AND L15 CSS SAM
L17 188039 S L14 AND L15 CSS FUL
L18 STR L14
L19 50 S L18 CSS SAM SUB=L17
L20 6576 S L18 CSS FUL SUB=L17
SAV TEMP L20 BERN526A/A
L21 STR L18
L22 SCR 1992 OR 2016 OR 2021 OR 2026
L23 50 S L21 NOT L22 CSS SAM SUB=L20
L24 SCR 2068 OR 2070
L25 50 S L21 NOT (L22 OR L24) CSS SAM SUB=L20
L26 3070 S L21 NOT (L22 OR L24) CSS FUL SUB=L20
SAV TEMP L26 BERN526B/A
L27 STR
L28 31 S L27 SAM SUB=L26
L29 621 S L27 FUL SUB=L26
SAV TEMP L29 BERN526C/A

17 july 2008

L30 2449 S L26 NOT L29
 L31 STR L18
 L32 50 S L31 CSS SAM SUB=L30
 L33 2360 S L31 CSS FUL SUB=L30
 SAV TEMP L33 BERN526D/A
 L34 STR L14
 L35 50 S L34 CSS SAM SUB=L33
 L36 942 S L34 CSS FUL SUB=L33
 SAV TEMP L36 BERN526E/A
 L37 7 S L13 AND NC>=2 NOT L36
 L38 6 S L37 NOT 26249-38-7
 L39 887 S L36 NOT (C8H8 OR C10H10)
 L40 643 S L39 AND NC>=3
 L41 622 S L40 NOT UNSPECIFIED
 L42 476 S L41 NOT (818-61-1 OR 79-10-7 OR 79-41-4)/CRN
 L43 442 S L42 NOT 868-77-9/CRN
 L44 STR L14
 L45 17 S L44 CSS SAM SUB=L43
 L46 197 S L44 CSS FUL SUB=L43
 SAV TEMP L46 BERN526F/A
 L47 245 S L43 NOT L46
 L48 159 S L47 AND O>=3
 L49 86 S L47 NOT L48
 L50 81 S L49 NOT C2H3CL
 L51 7 S L50 AND 1/O
 L52 74 S L50 NOT L51
 L53 12 S L52 AND (CL OR BR OR I)/ELS
 L54 62 S L52 NOT L53
 L55 19 S L54 AND (C5H8 OR C10H10O2 OR C4H6O2 OR C18H20 OR C12H22O2 OR
 SEL RN 1 5-9 13-15 18 19
 L56 11 S E14-E24
 L57 51 S L54 NOT L56
 L58 57 S L38,L57
 SAV TEMP L58 BERN526G/A
 L59 3 S L13 AND L57
 L60 51 S L57,L59
 L61 4 S L13 NOT L60,L58
 L62 3 S L61 NOT C2H2F2
 L63 2 S L62 NOT C5H8O2
 L64 53 S L60,L63
 L65 1 S L62 NOT L64
 L66 6 S L58 NOT L64

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 L69 1 S L67 AND PY<=2002 NOT P/DT
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 L71 34 S L57 AND (PD<=20020905 OR PRD<=20020905 OR AD<=20020905) AND P
 L72 5 S L1-L12 AND L67
 L73 37 S L68-L71
 L74 4 S L72 AND L73
 L75 5 S L72,L74
 L76 33 S L73 NOT L75

FILE 'HCAPLUS' ENTERED AT 10:05:37 ON 17 JUL 2008

FILE 'REGISTRY' ENTERED AT 10:06:19 ON 17 JUL 2008

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17 july 2008